

ASPDAC 2007 Keynote

Next-Generation Design and EDA Challenges:

Small Physics, Big Systems, Tall Toolchains

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About This Talk...

- There are **three** different kinds of keynote talks...



#1: Explain A Big Problem

- Continued CMOS device scaling is getting *tough*...



- Leakage, variation, reliability, cost...

#2: Predict the Future

■ Fun...

...but *difficult*



#3: Offer Some Advice



Good advice



New ideas



Different ideas



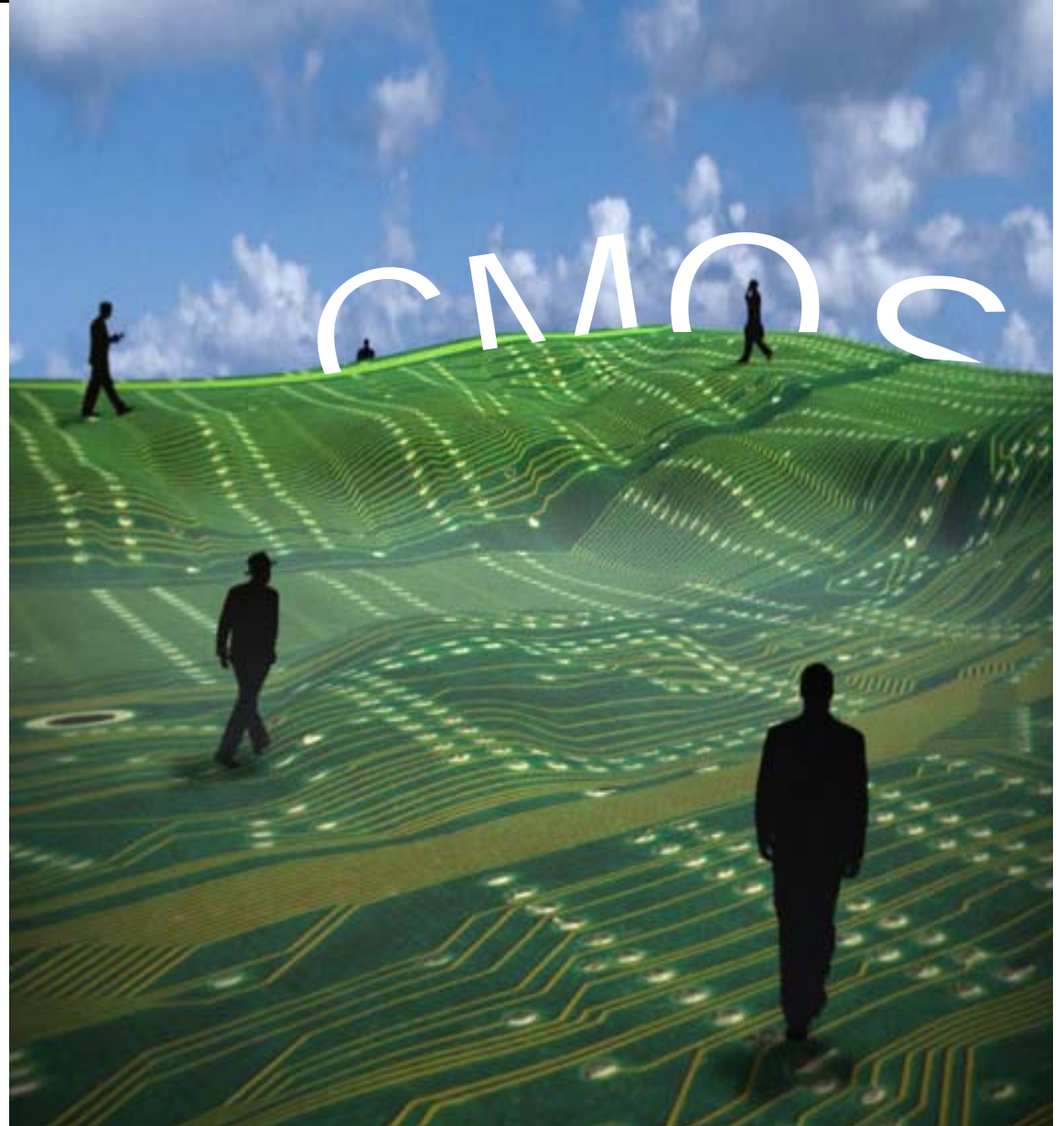
(Interesting, too)

This Is An *Advice* Talk

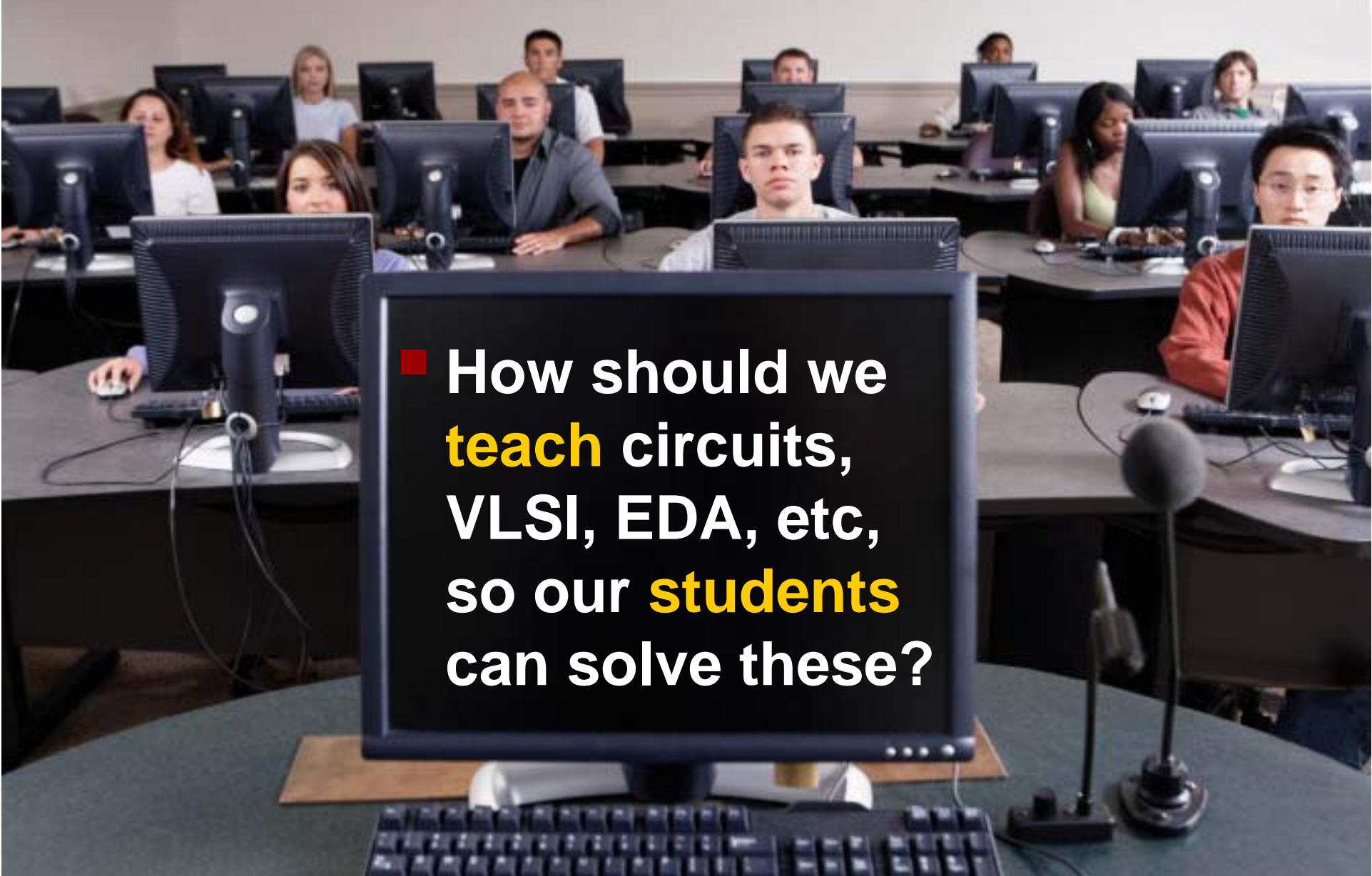
As we near the
end of the silicon
roadmap...

What *kinds* of
problems are the
big challenges?

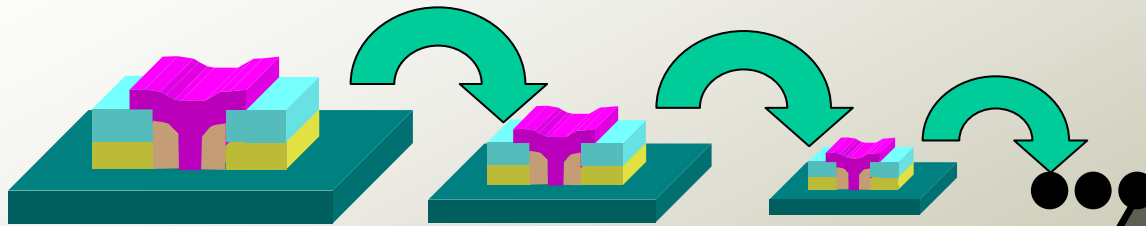
What *styles* of
problem-solving
might work best?



Secondary, Personal Motivation

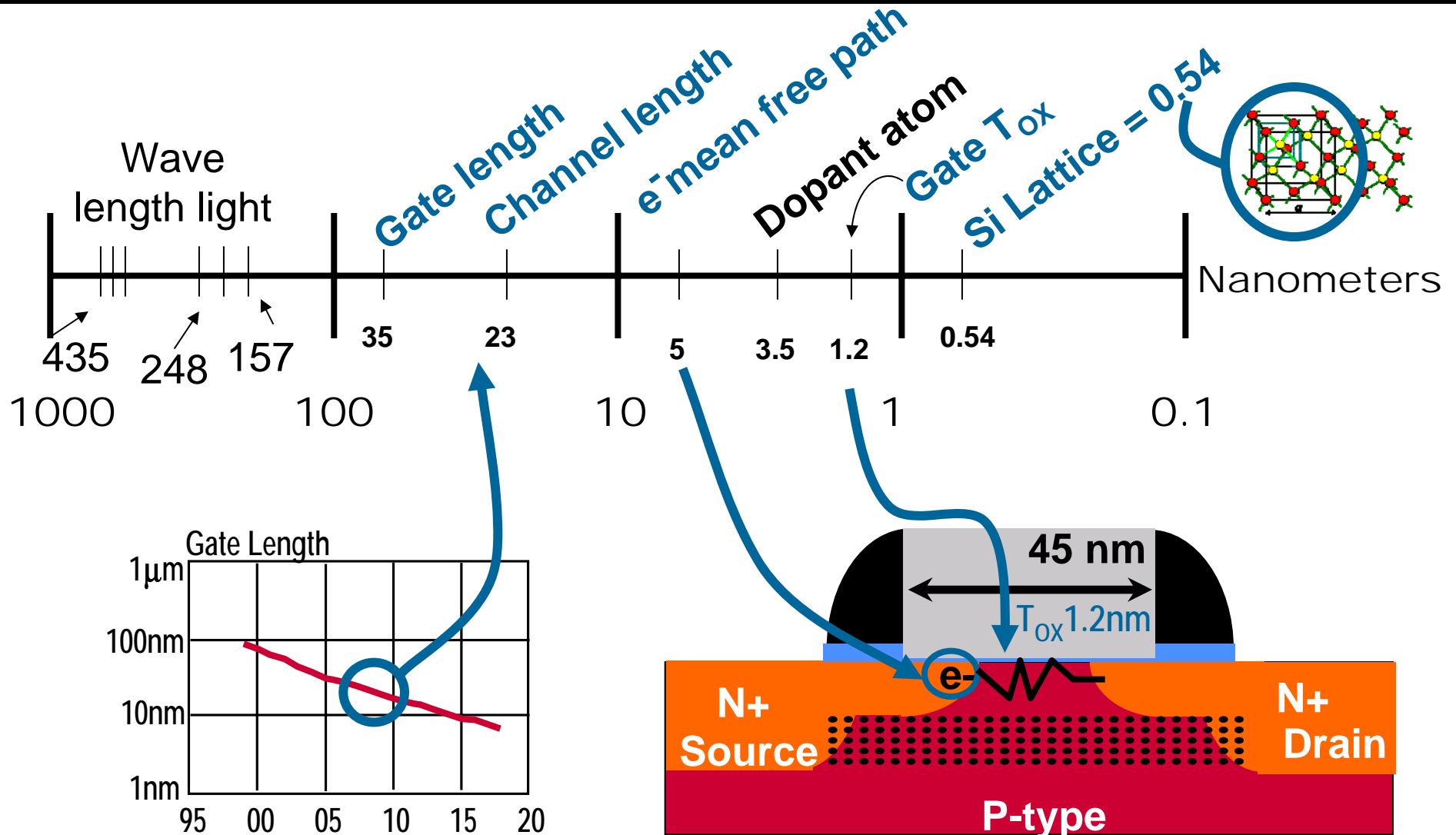
- 
- A photograph of a computer lab with several students sitting at desks with computers. In the foreground, a computer monitor displays a text box with a question. The background shows other students working at their computers.
- How should we **teach** circuits, VLSI, EDA, etc, so our **students** can solve these?

Big Challenge #1: Small Physics



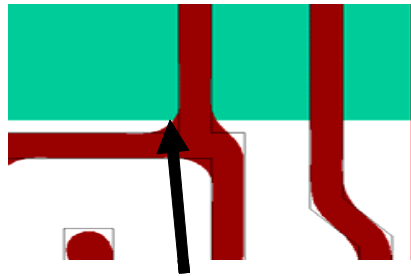
■ **Challenges**
in performance,
in manufacturing,
in predictability,
in cost...

Approach *Atomic* Scale → *Challenges*

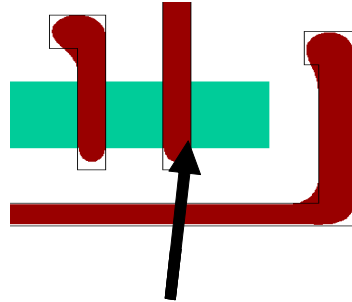


[Source: Scott Thompson, U Florida]

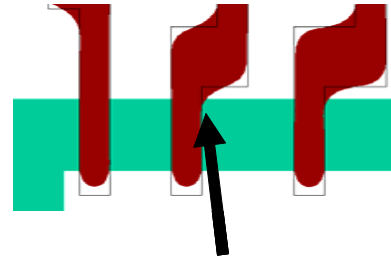
One Challenge: Mask Variability & Cost



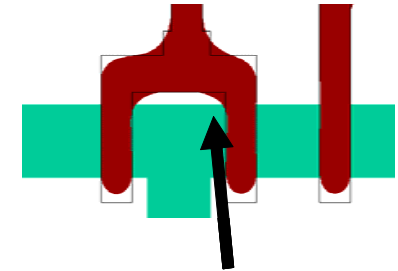
**Sensitive to grow
due to defocus**



**Sensitive to shrink
due to defocus**



**Sensitive to
exposure variation**



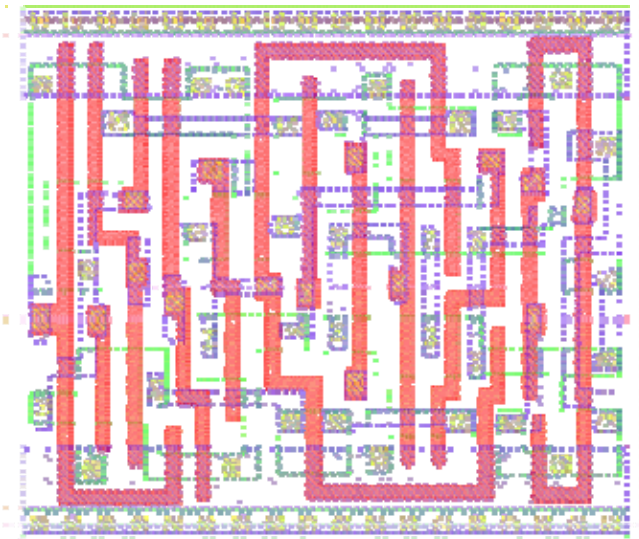
**Sensitive to
resist effects**

- **Standard geometry rules may *not* be enough**
 - **DRC rules very complex; get worse with scaling**
 - **Sub-wavelength lithography; neighbor interactions**

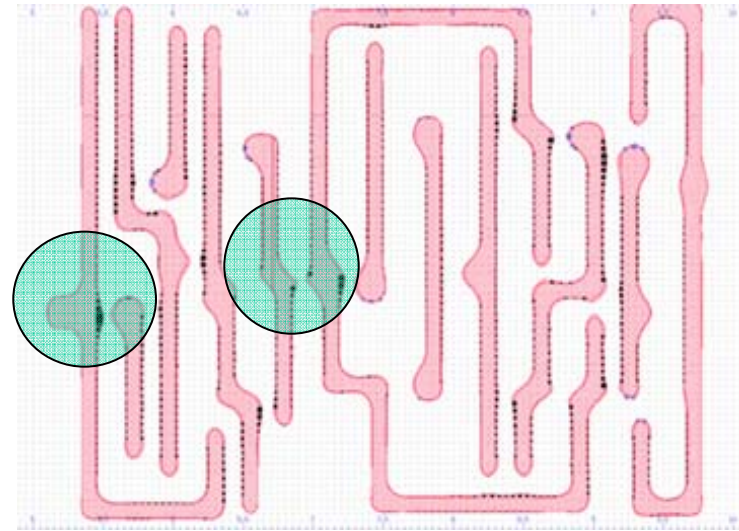
[Source: Larry Pileggi, Andrzej Strojwas, CMU]

The Mask Variability/Cost Challenge

- **Big problems on even simple circuits**
 - **Performance (e.g., leakage), yield compromised**



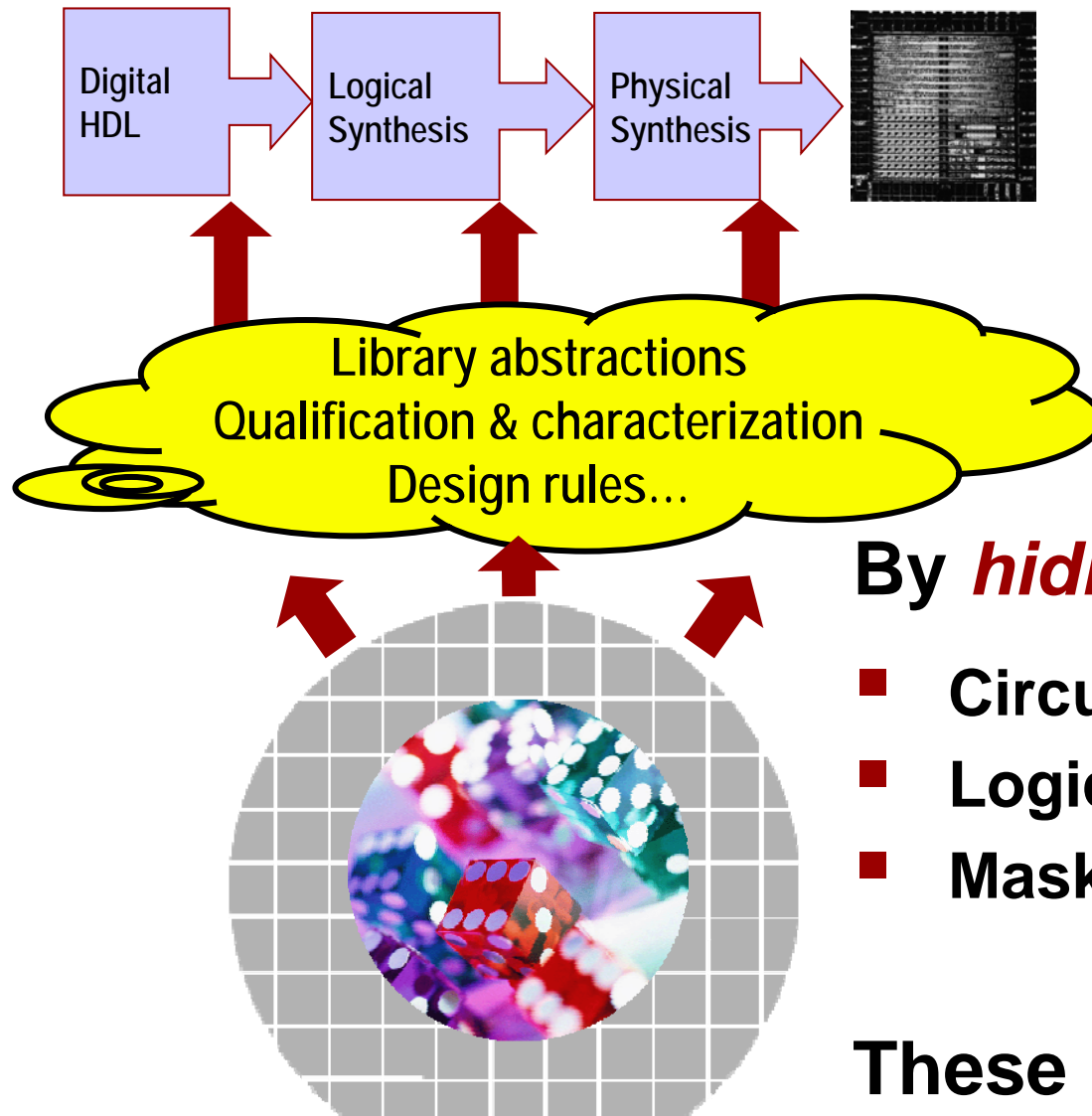
Typical standard cell



**Printability problems
from lithography simulation**

[Source: Larry Pileggi, Andrzej Strojwas, CMU]

How Did We Handle This Until Now...?



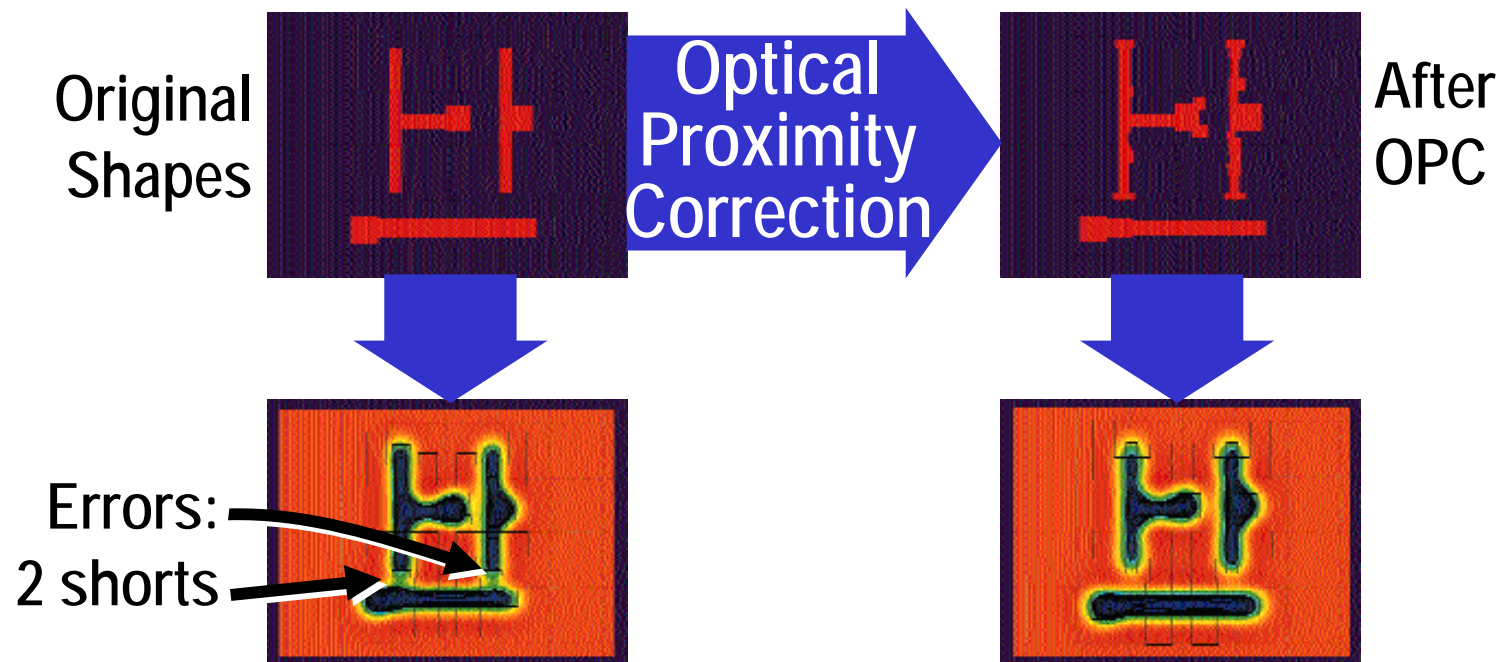
By *hiding & abstracting*

- Circuit & shapes **rules**
- Logic/memory **libraries**
- Mask/circuit/logic **isolated**

These ideas starting to *fail*

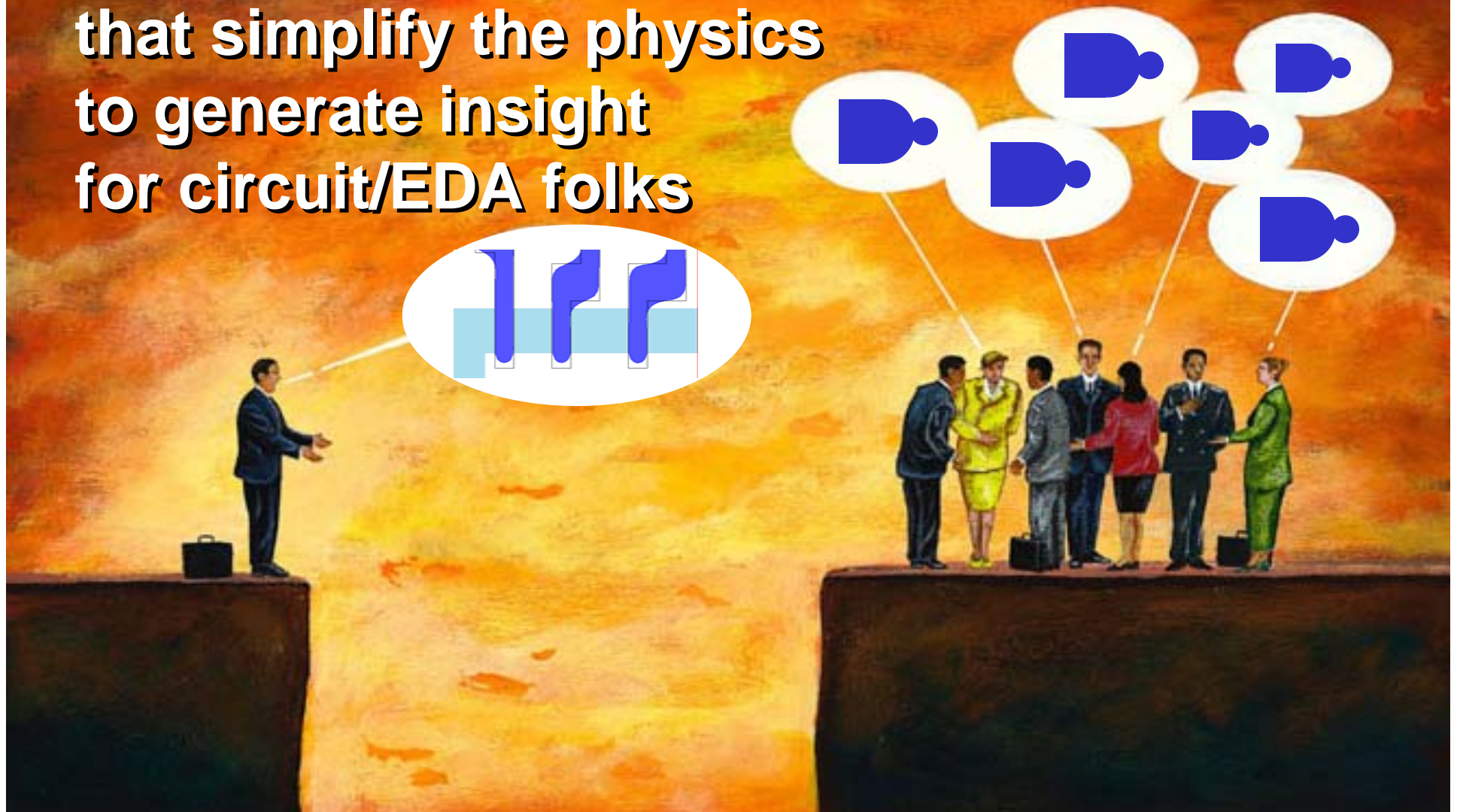
How to Explain (*Teach*) This...?

- Before nanoscale CMOS, masks were simple
 - Today, cannot make a mask without complex *Resolution Enhancement Technology* (RETs)



"Small Physics" Advice

- Build some **bridges** that simplify the physics to generate insight for circuit/EDA folks



Some Useful Insight...

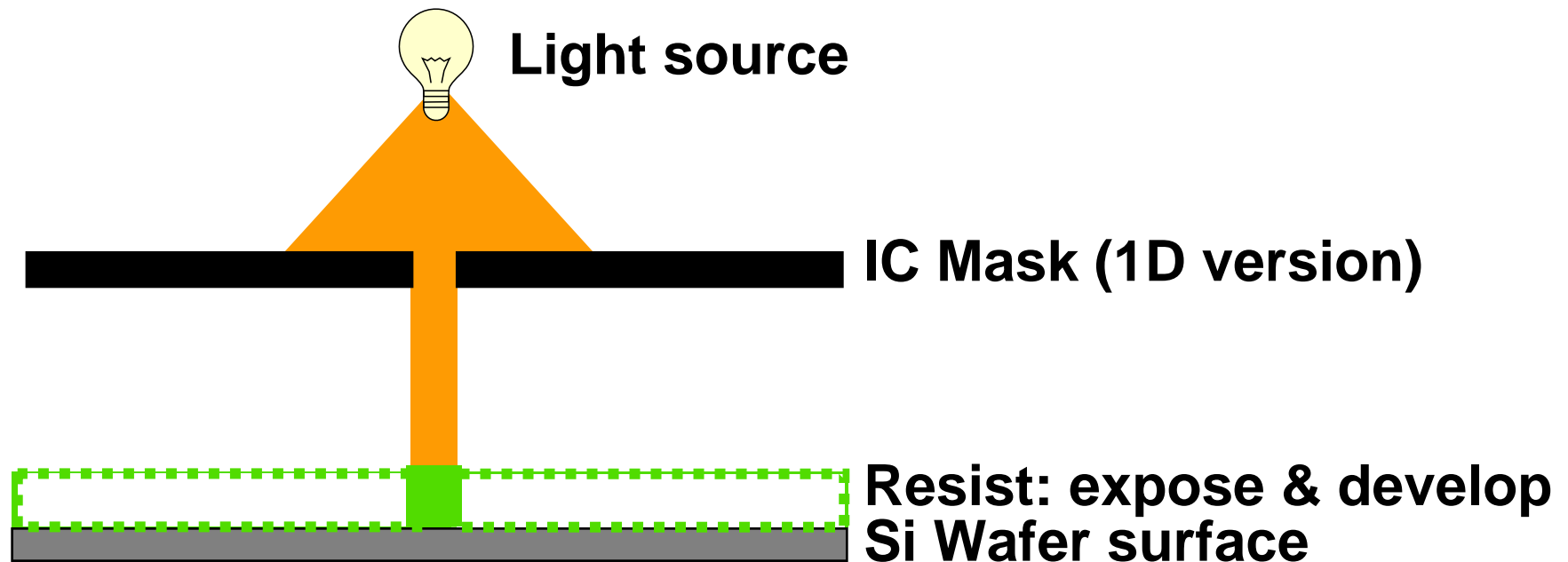
“One thing we know about **creativity** is that it typically occurs when people who have mastered two or more quite **different** fields use the framework in one to think afresh about the other...

Marc Tucker, *Tough Choices or Tough Times*

- So: Lithography + circuits/CAD/optimization?

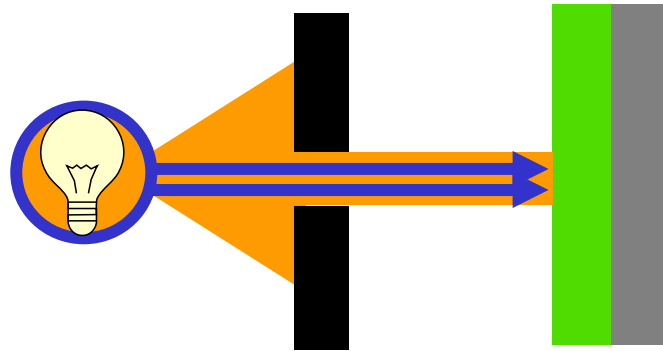
Example: Vastly Simplified Litho Model

- Light source + 1D mask + photoresist



Unpleasant Physical Realities

- Light does *not* travel in nice straight lines

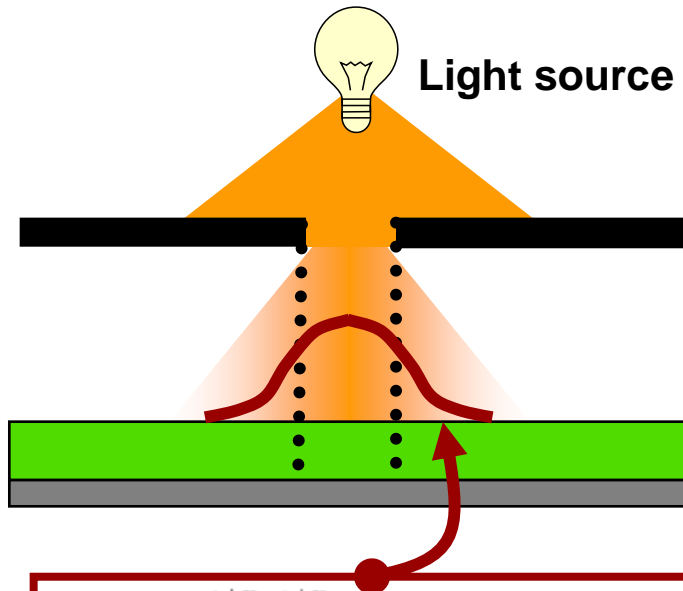


- Resist *not* infinitely sensitive to light



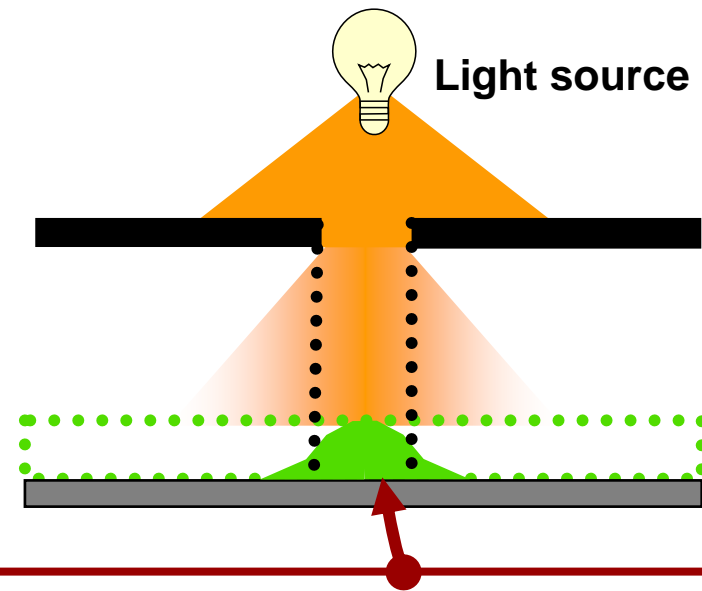
Light *Bends* and Resist is *Nonlinear*

Light intensity delivered
is complex function of
litho optics



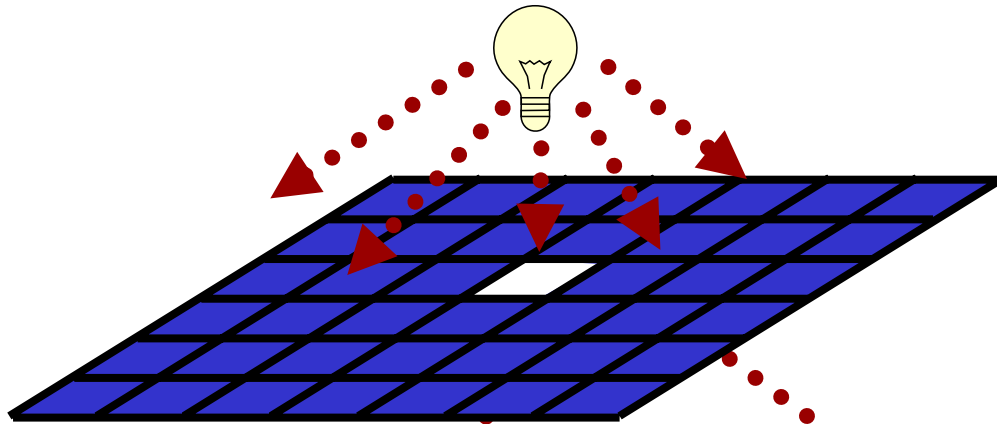
$$I(f, g) = \int_{-\infty}^{+\infty} \int_{-\infty}^{+\infty} T(f' + f, g' + g; f', g') \\ \cdot F(f' + f, g' + g) F^*(f', g') df' dg' \\ I(x, y) = \mathfrak{F}^{-1}[I(f, g)]$$

Resist response is
complex function of
light delivered

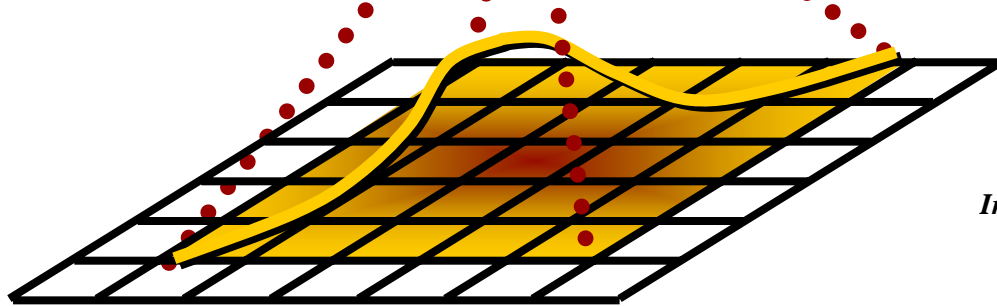


**Complex optics + chemistry
= Complex mask shape**

To Get Some Insight: *Simplify*

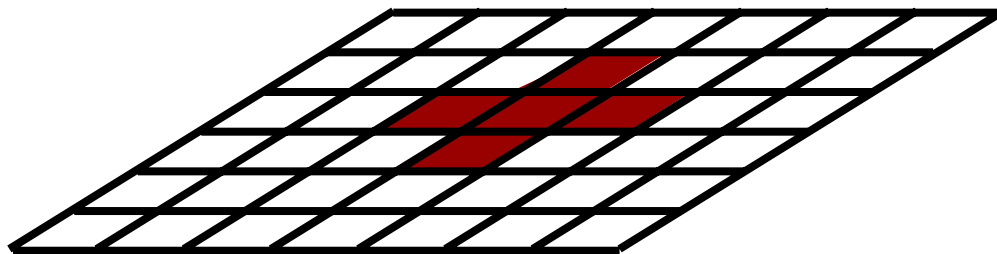


Pixeled binary mask

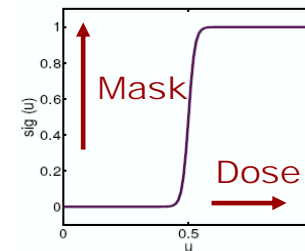


Additive Gaussian blur optics

$$Intensity(\Delta x, \Delta y) = N \cdot \left[\frac{1}{\sqrt{2\pi\sigma^2}} e^{-\frac{(\Delta x)^2}{2\sigma^2}} \cdot \frac{1}{\sqrt{2\pi\sigma^2}} e^{-\frac{(\Delta y)^2}{2\sigma^2}} \right]$$

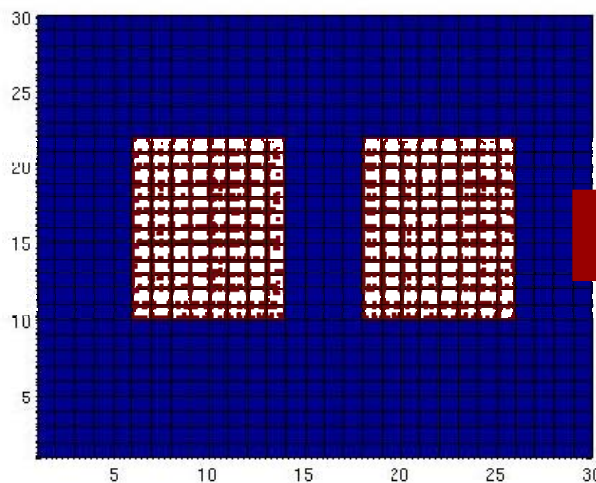


Simple resist threshold

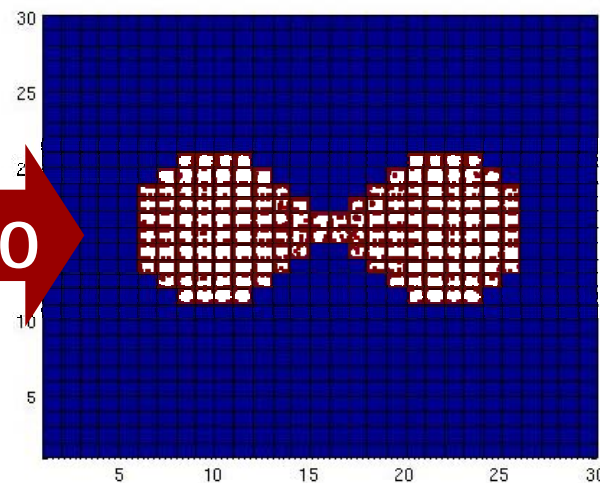


A Nice CAD Class Project: OPC

- Optical Proximity Correction
 - *Inverse mask* problem: given shapes, *derive* mask
 - Turn pixels on/off with simple optimizer (inspired by early OPC+annealing ideas of Zakhor et al, Berkeley)



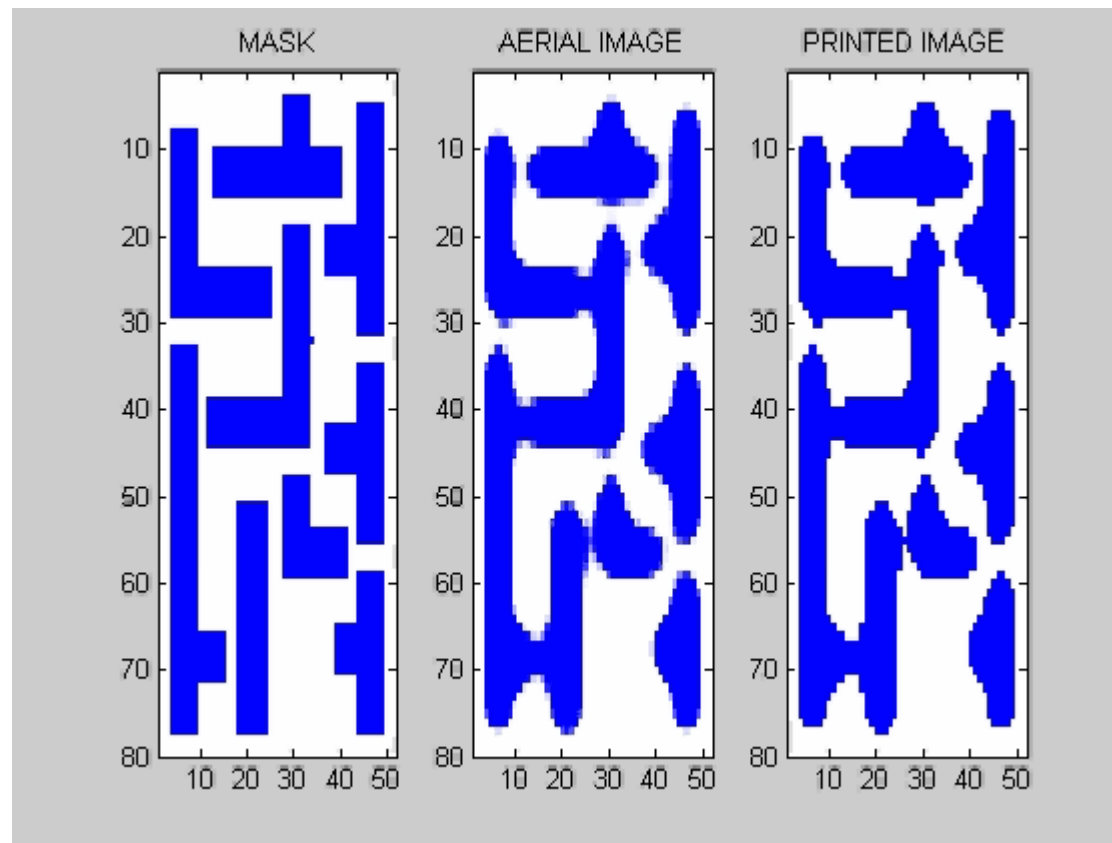
Cannot just
use desired shapes



"Fake" physics model
gives realistic aerial image

Even with “Fake” Physics: Useful

- **Excellent litho insights for circuit/EDA people**



[Source: Sonia Singhal, CMU]

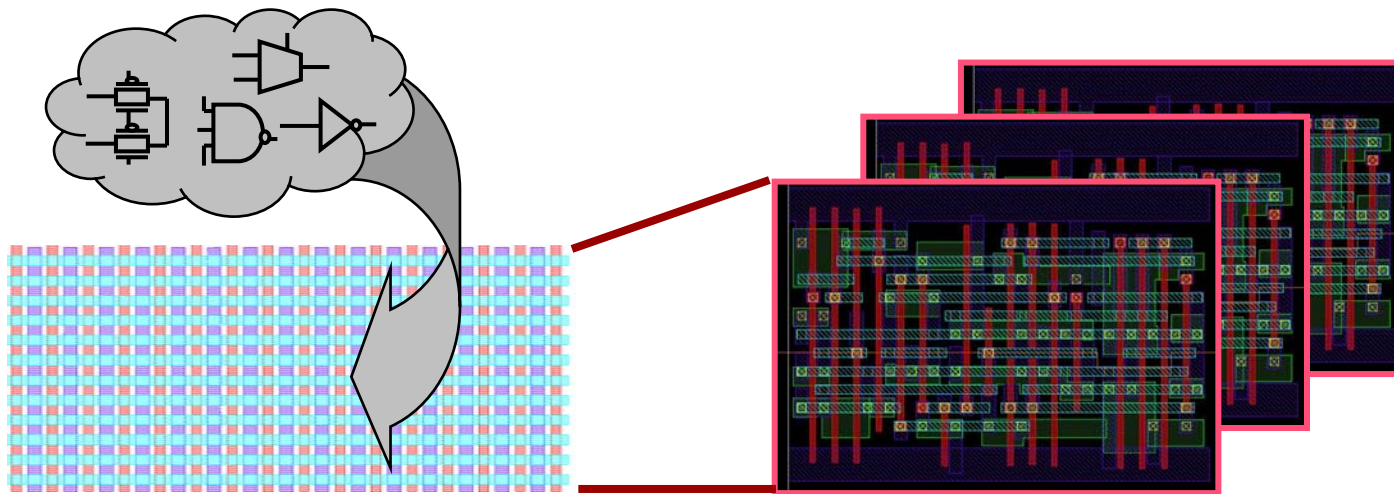
Why This Matters: Regular Circuits

- Next generation of designs may rely on a totally new idea: regular circuit fabrics, where all transistors ~~~identical~~



Example: CMU Regular Logic “Bricks”

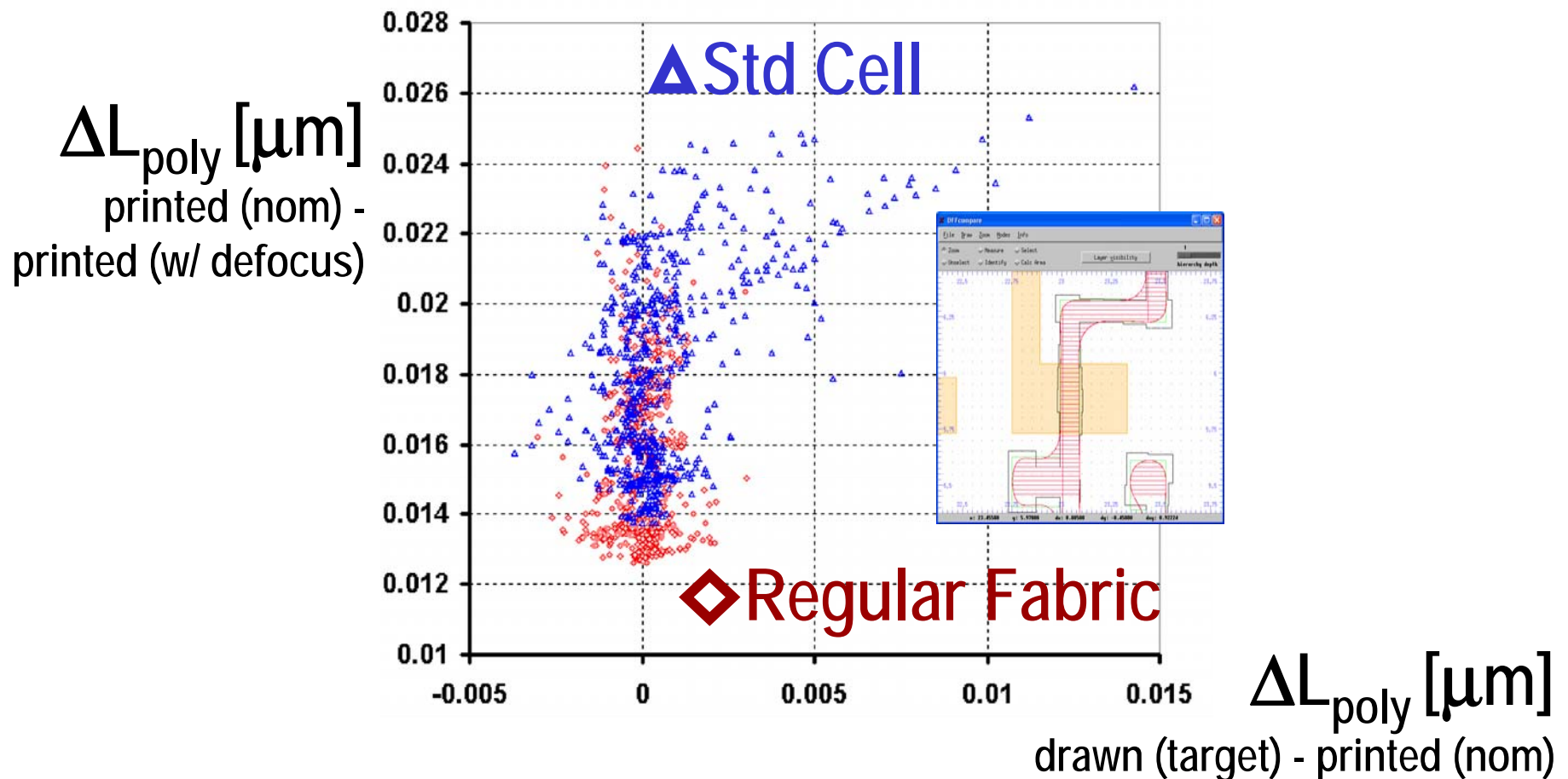
- Small, dynamically compiled, *litho-regular*, configurable logic lib, few geometry patterns
- Design flow requires novel tools, algorithms



[Source: Larry Pileggi, Andrzej Strojwas CMU]

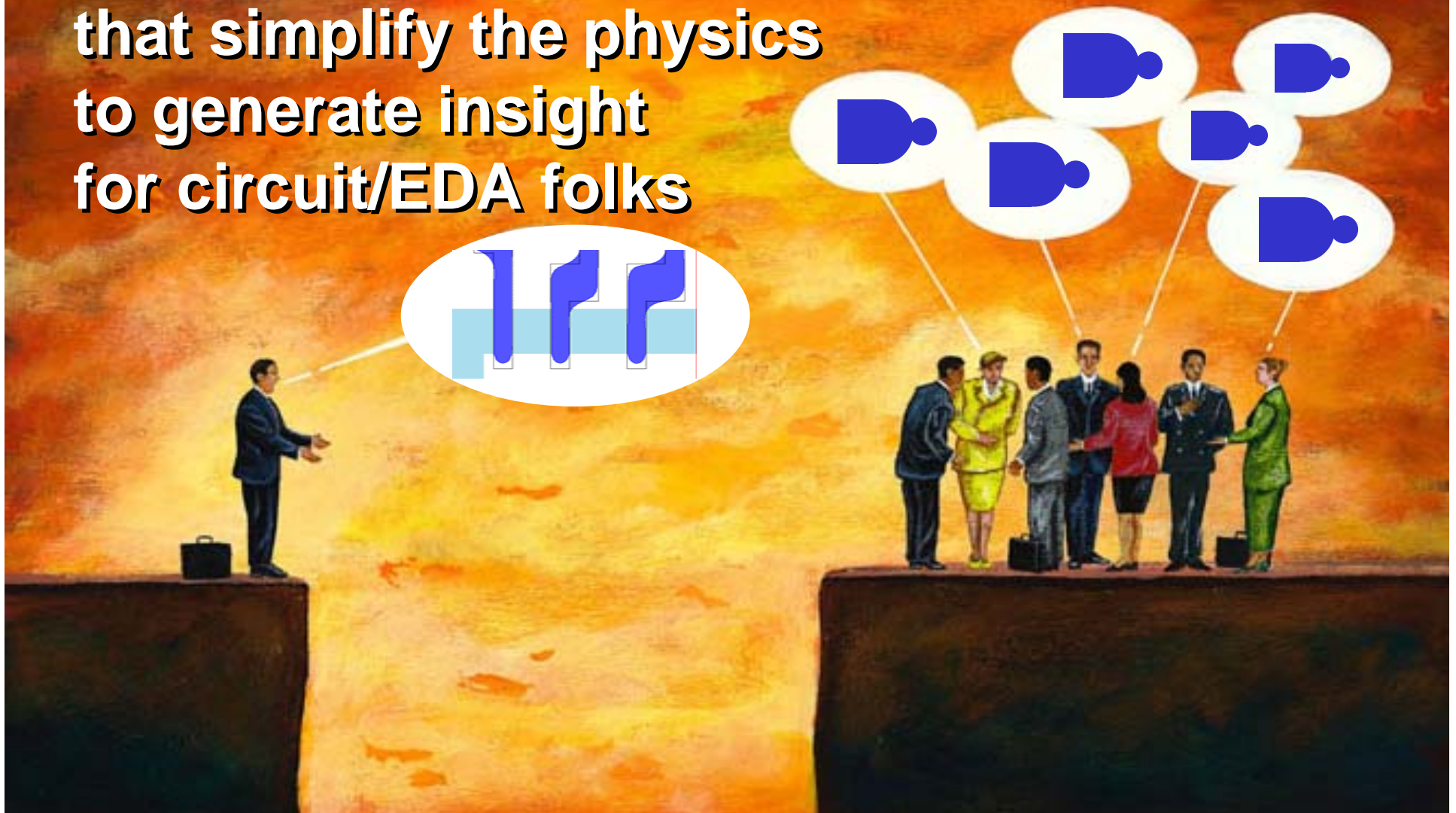
Early Results from Regular Bricks

- Dramatically better L_{eff} control → Lower leakage

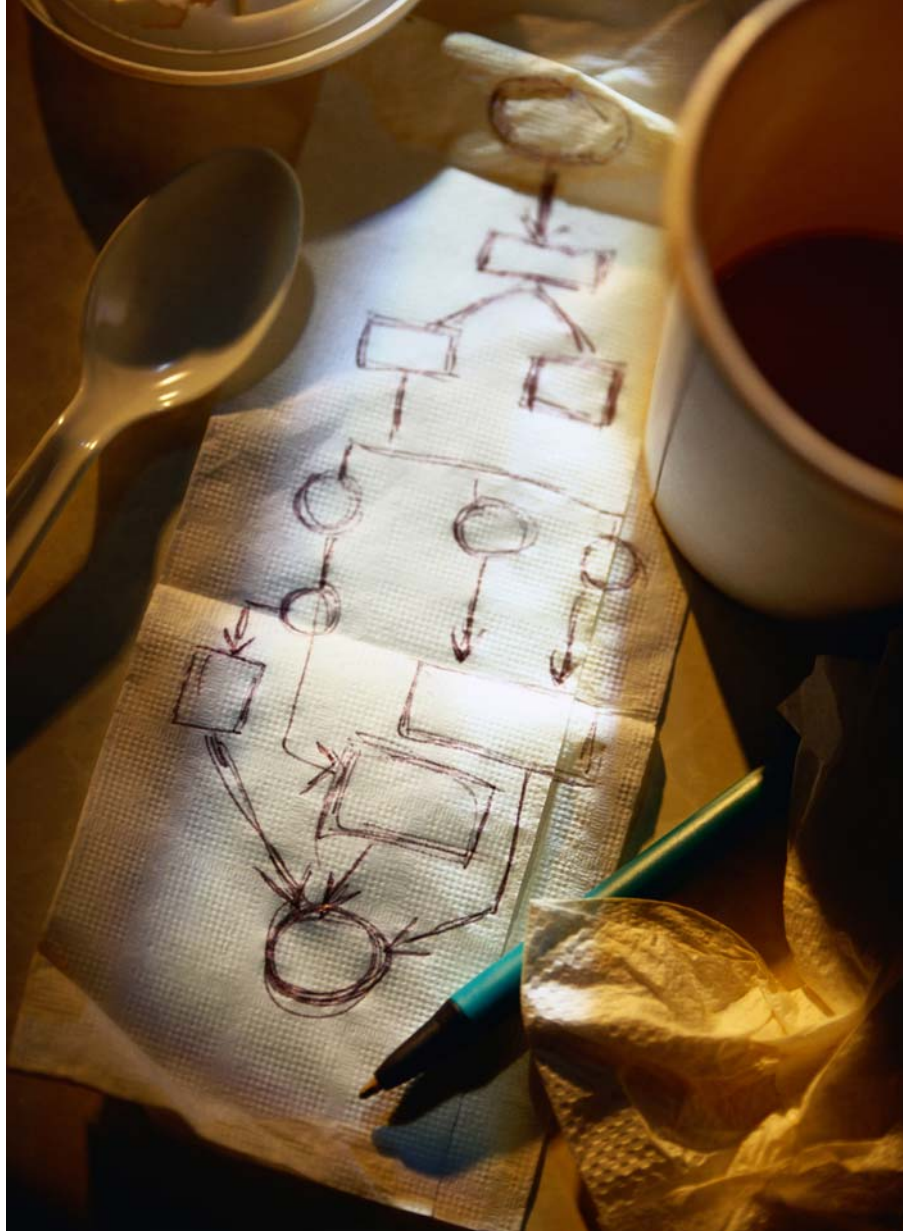


"Small Physics" Advice

- Build some **bridges** that simplify the physics to generate insight for circuit/EDA folks



Big Challenge #2: Tall Tool-Chains

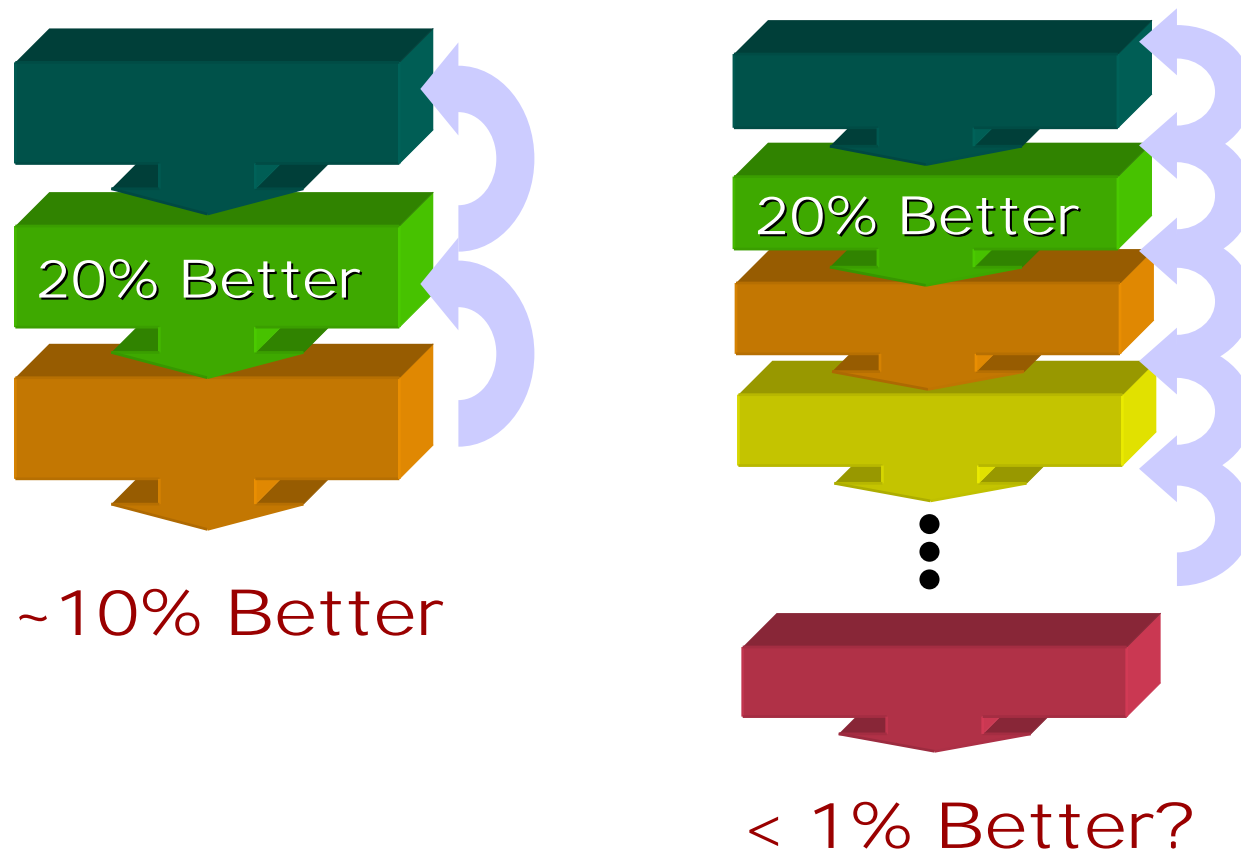


The sets of CAD tools we use to do big designs are ***not simple*** anymore

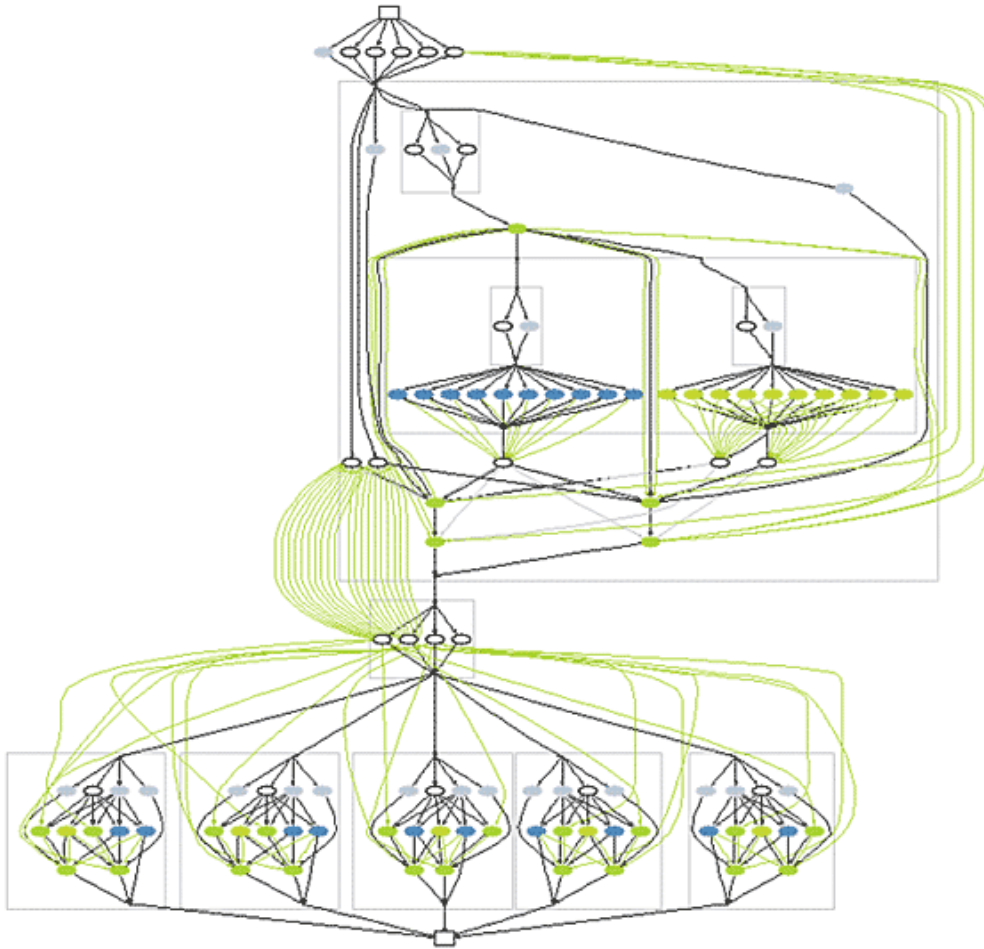
This complexity poses new problems for ***tool innovation***

Rutenbar's *Rule of Attenuation*

- The taller the tool-chain, the more difficult for innovation in 1 tool to “survive the flow”

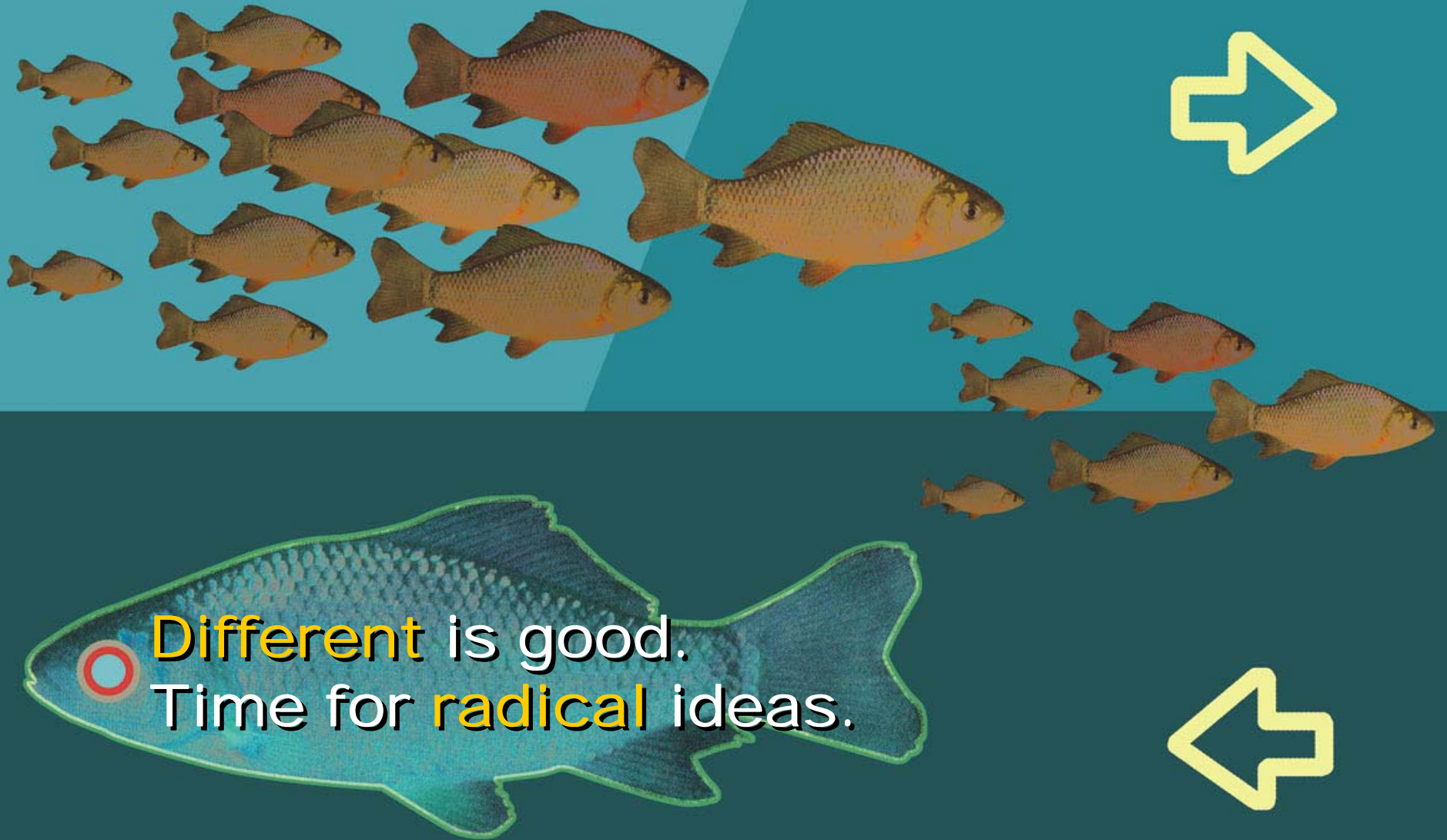


How “Tall” is Tall?



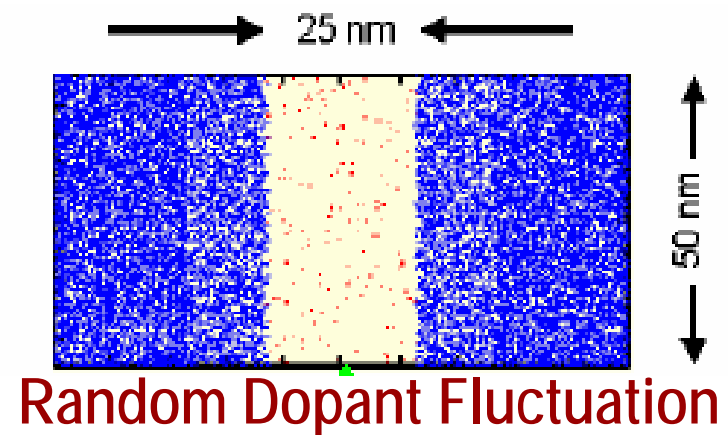
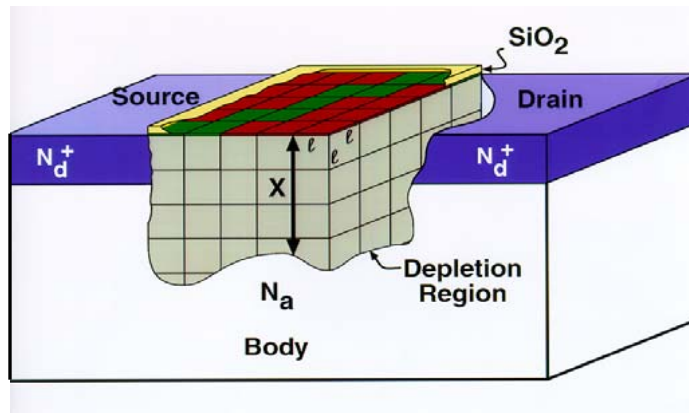
- **Very tall**
- **Very deep sets of connected tools, scripts, files, databases, sign-offs, etc**
- **Ex: 4000-step commercial design-flow**

"Tall Tool-Chains" Advice



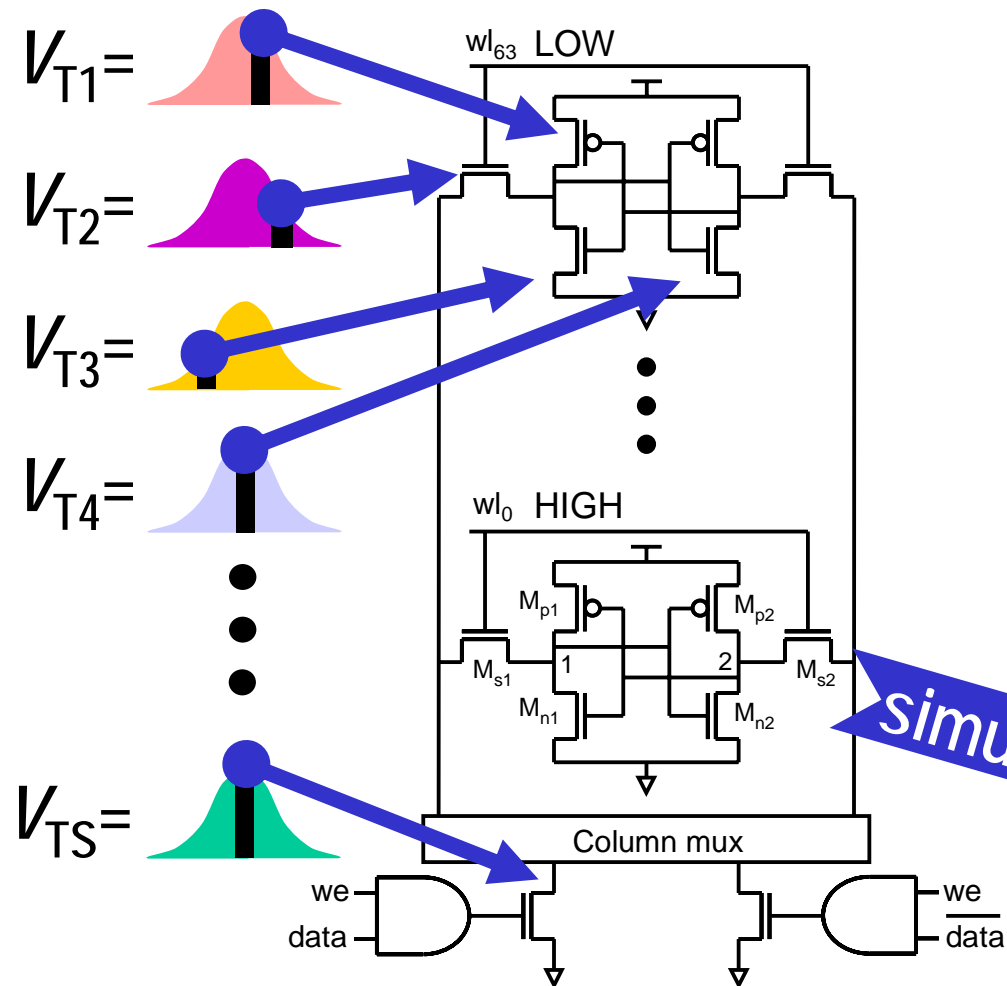
Back to a “Small Physics” Problem

- At nanoscale, *random disturbances* have a significant impact on devices



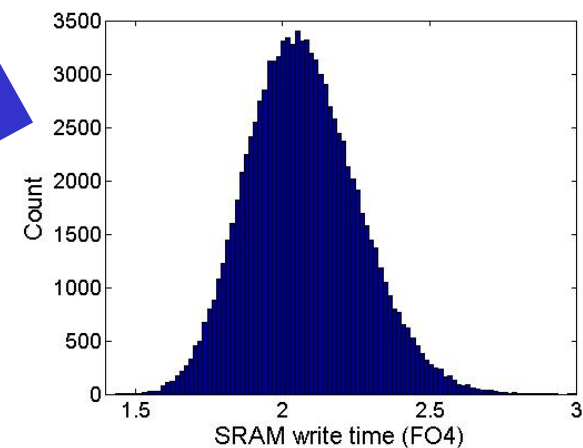
- How significant?
 - 25nm channels, $\sigma[V_T]$ uncertainty \rightarrow 10-20%
 - From [Wong, 1999 VLSI Tech. Symposium]

To Evaluate Circuit Impact: Monte Carlo

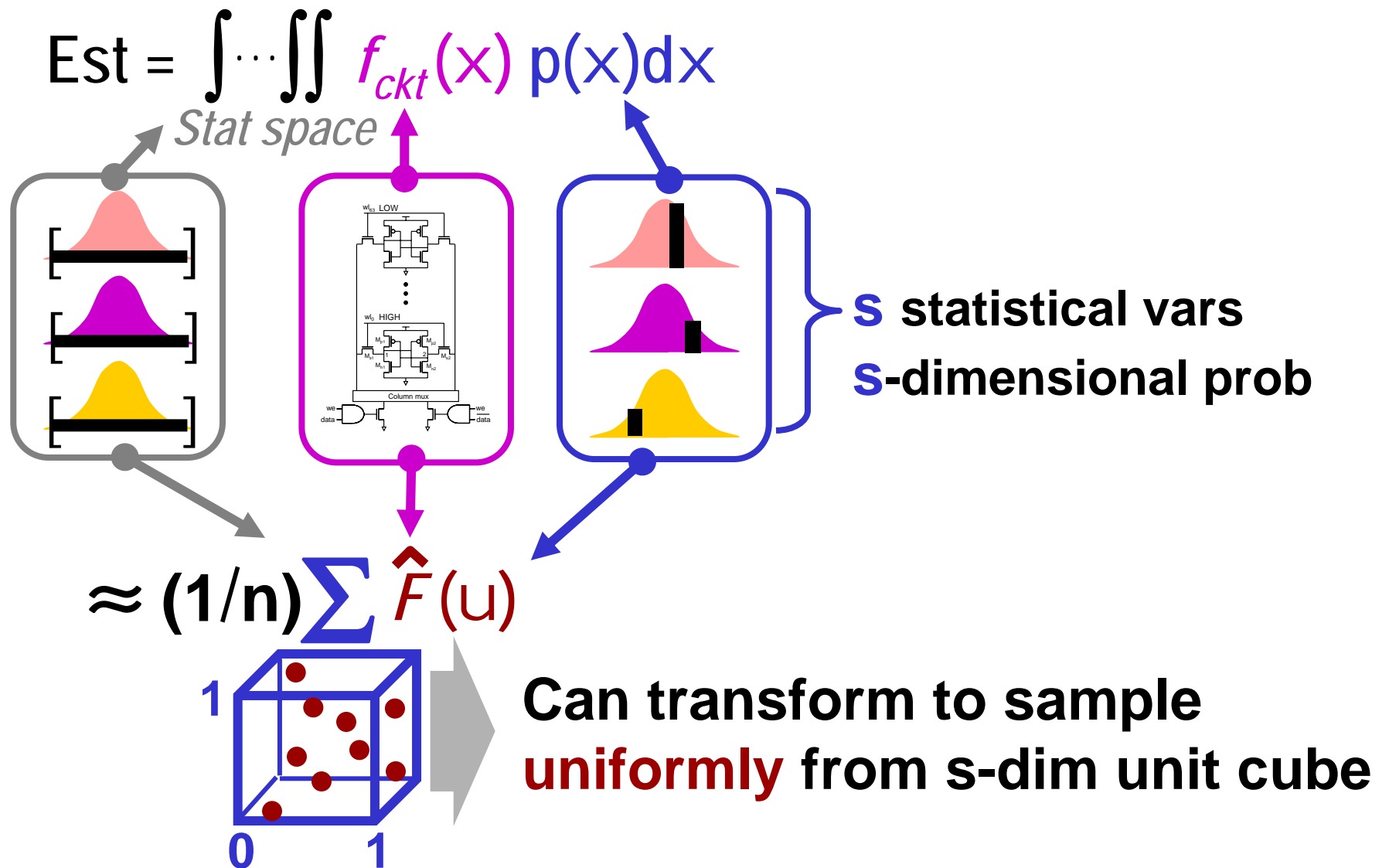


- Sample each statistical variable
- Parameterize one circuit, simulate it
- Repeat--n samples

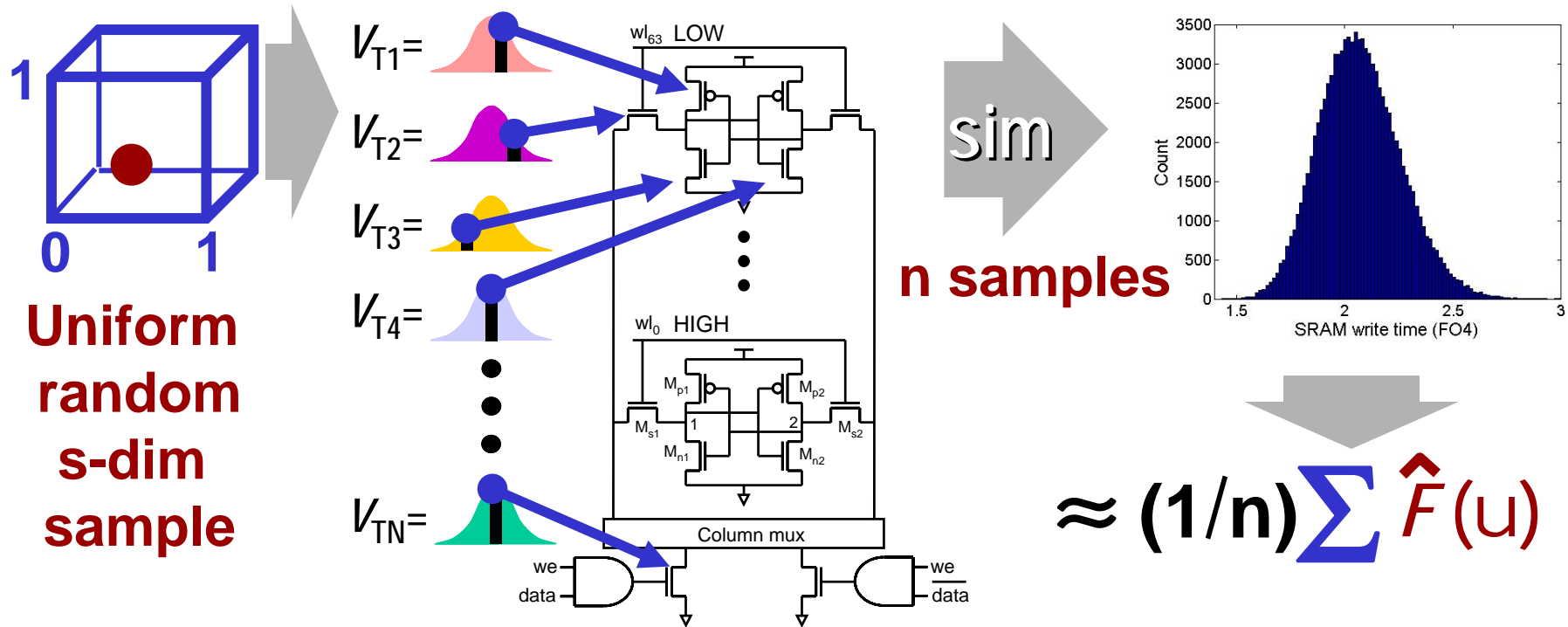
simulate



Monte Carlo Math: Just A Big Integral



Evaluate Circuit Impact: Monte Carlo



- “Unit cube” thing seems like a *minor* detail
- ... but it turns out to be *crucial*

Why is Monte Carlo Difficult?

- High-dim problems: ***s** is big (100-1000)*
- Profoundly nonlinear: ***Nanoscale** physics*
- Accuracy matters: ***~1-5%** error*
- Speed matters: ***Many** samples*
- Samples expensive: ***Simulate** each circuit*

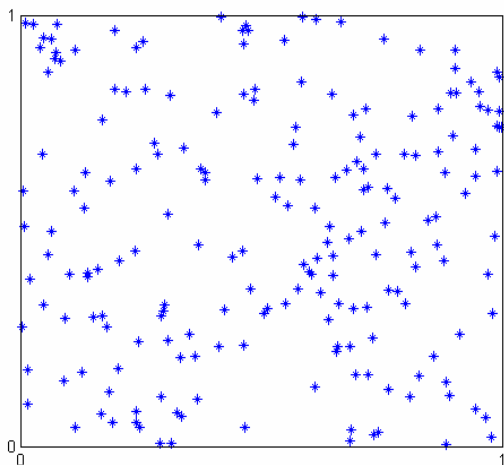
Question: Who *Else* Has This Problem?



Computational finance(!)

- Valuing complex financial instruments, derivatives
- High-dimensional, nonlinear, statistical integrals
- **Speed+accuracy** matters here, e.g., ~real-time decision-making

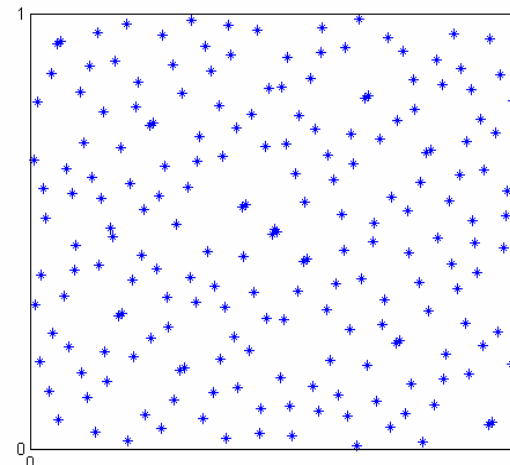
Big Idea: Quasi Monte Carlo (QMC)



- **Classical Monte Carlo**
 - Uniform pseudo-random pts
 - Surprise: **not** very uniform

- Error for n samples

$$O(1 / \sqrt{n})$$



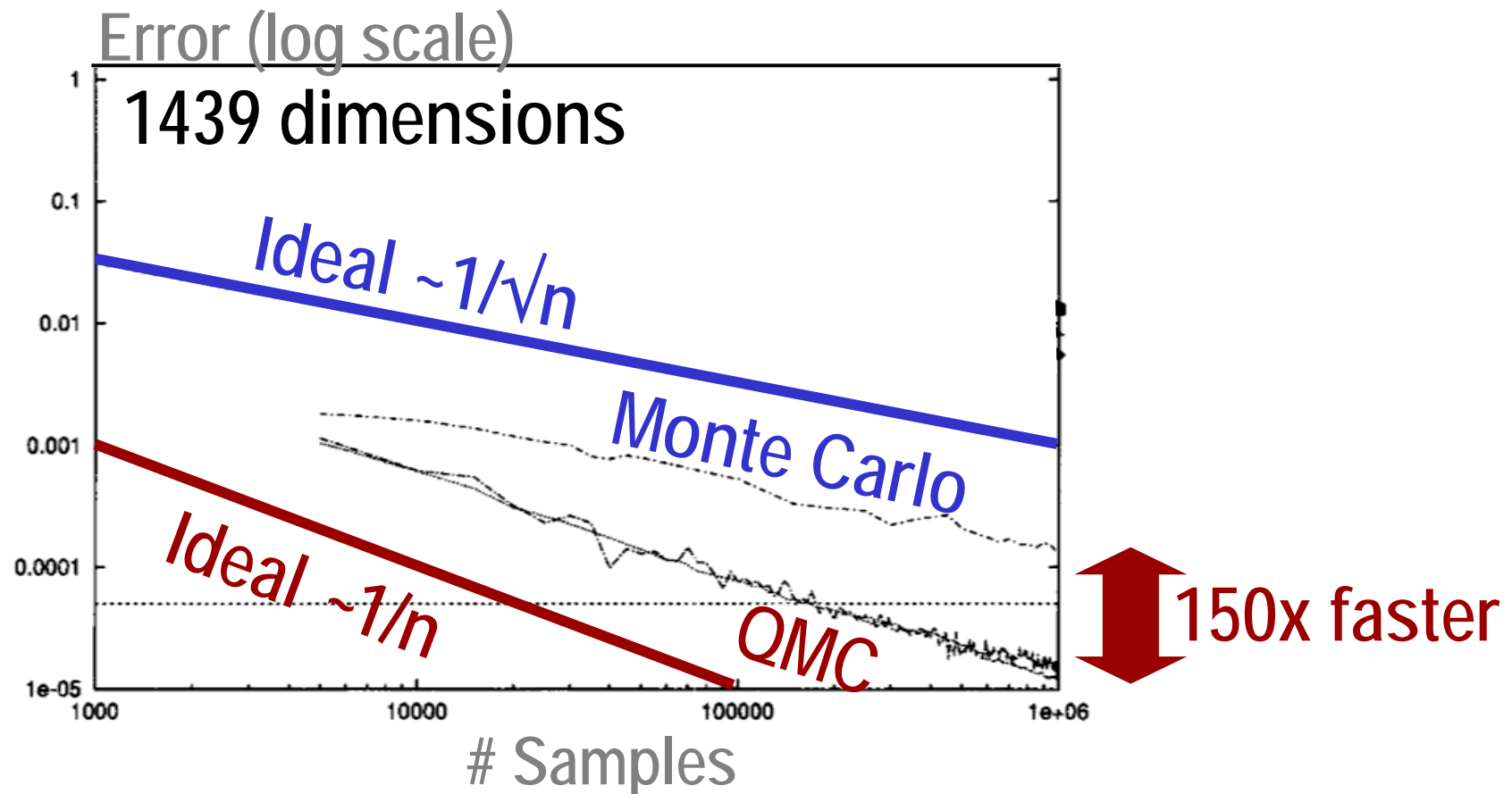
- **Quasi Monte Carlo**
 - **Deterministic** samples
 - “Low-discrepancy” pts

- Error for n samples

$$O(1 / n)$$

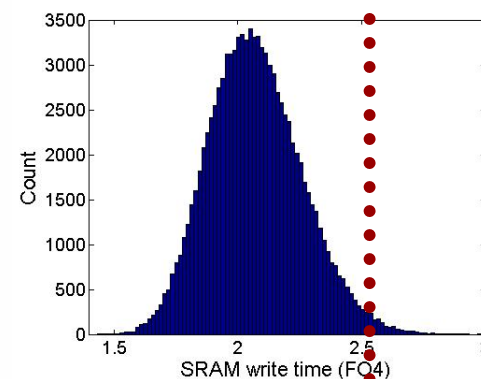
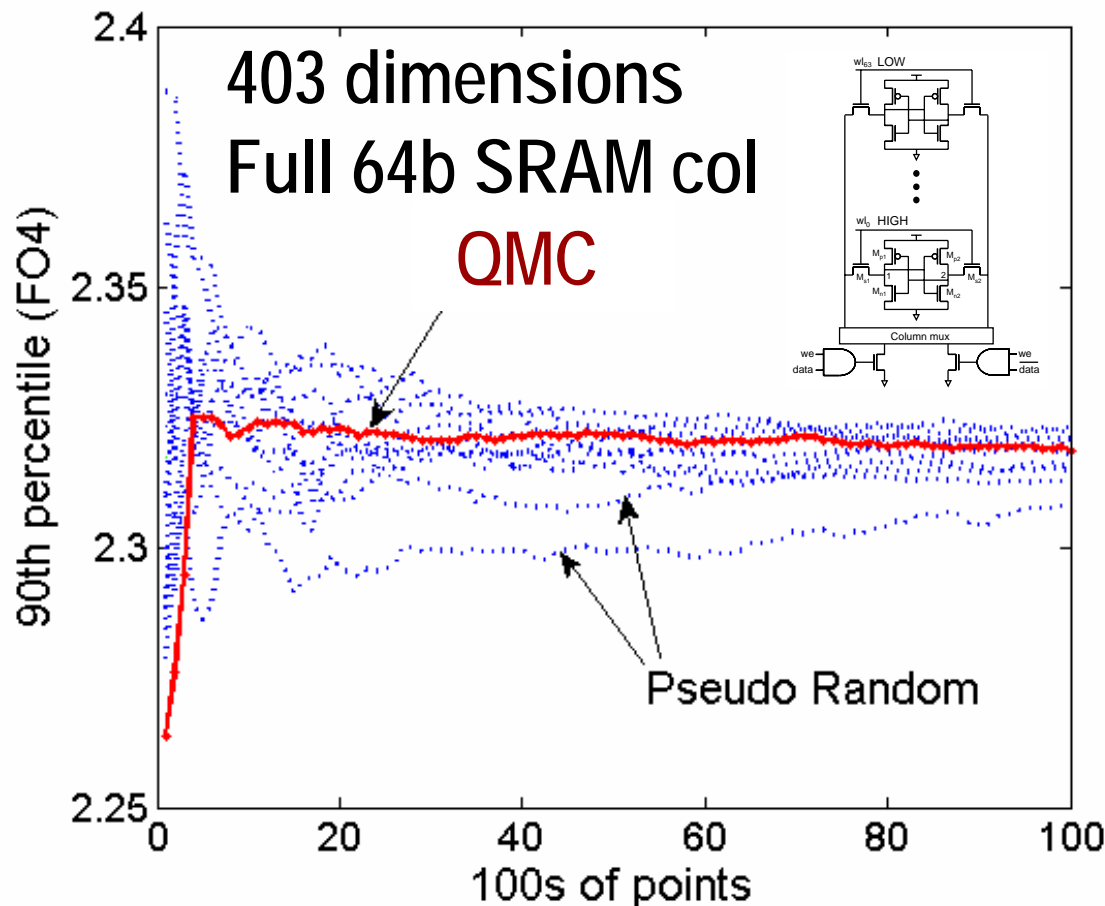
Computational Finance Example

- Eval 5-year discount price for a bond
 - From [Ninomiya, Tezuka, App Math Finance 1996]



Does It Work for Circuits? (Yes!)

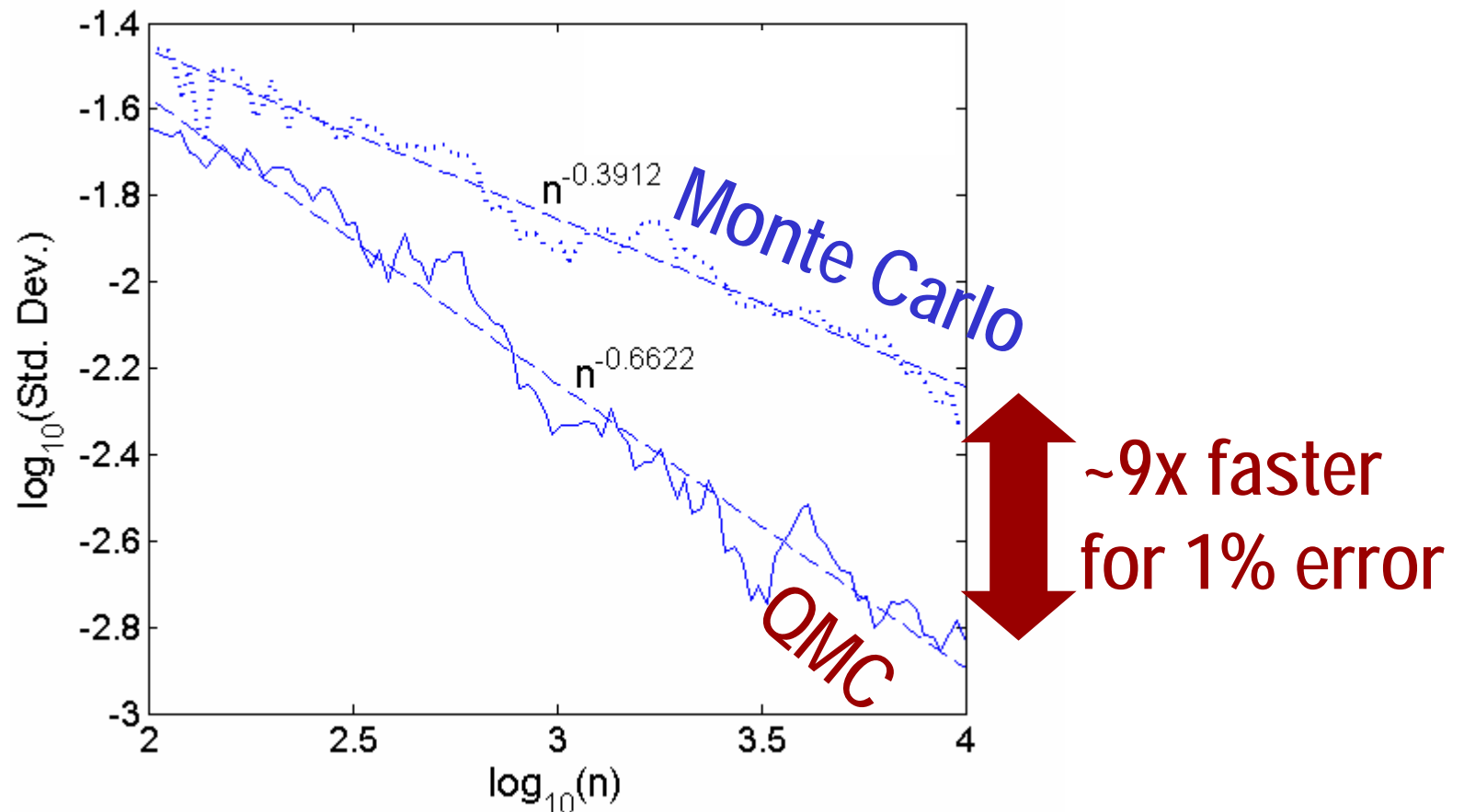
- But requires some subtlety to map to QMC
 - [Singhee, Rutenbar, ISQED 2007, to appear]



$$\Pr(\text{write} < t_w) = 0.9$$

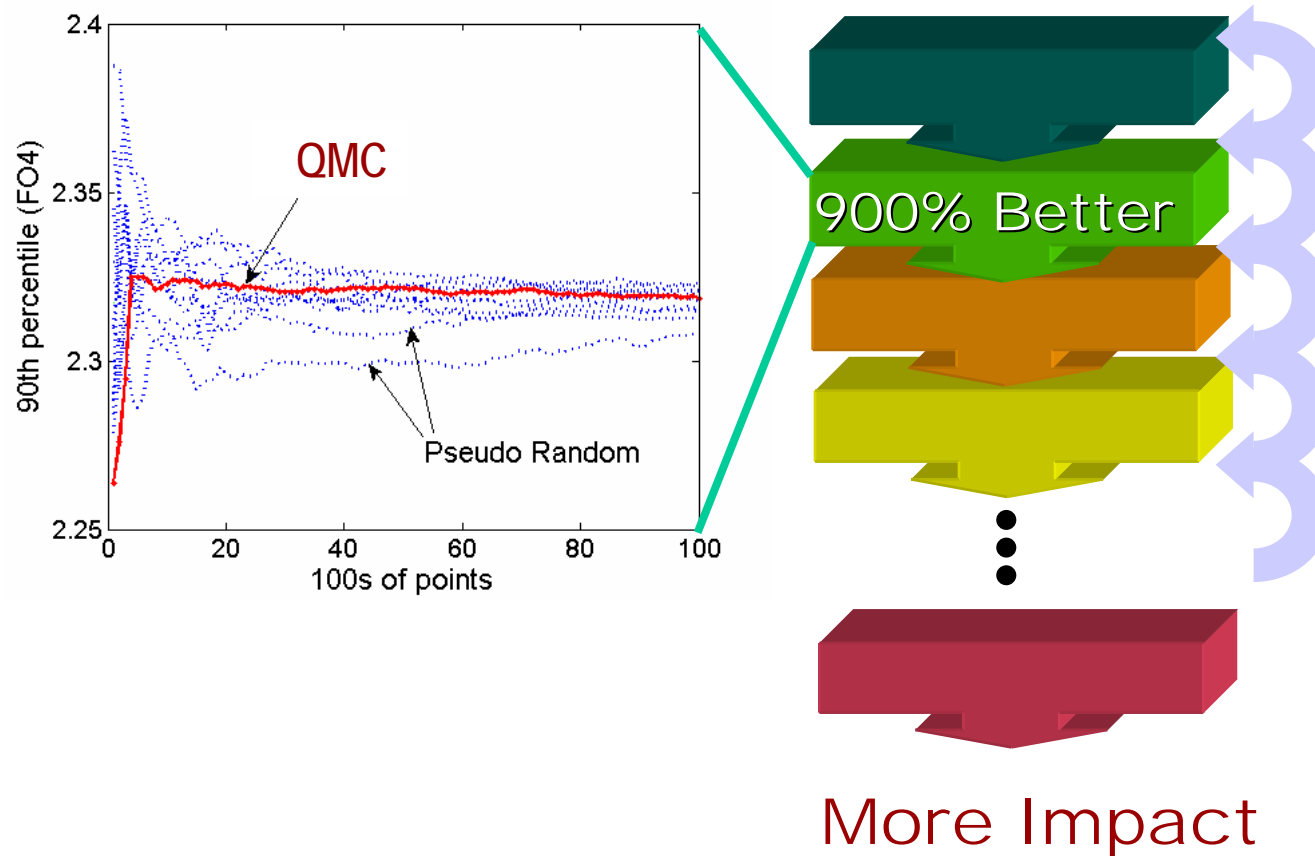
Very Promising Speedups

- Same 403-dimensional, 64b SRAM column

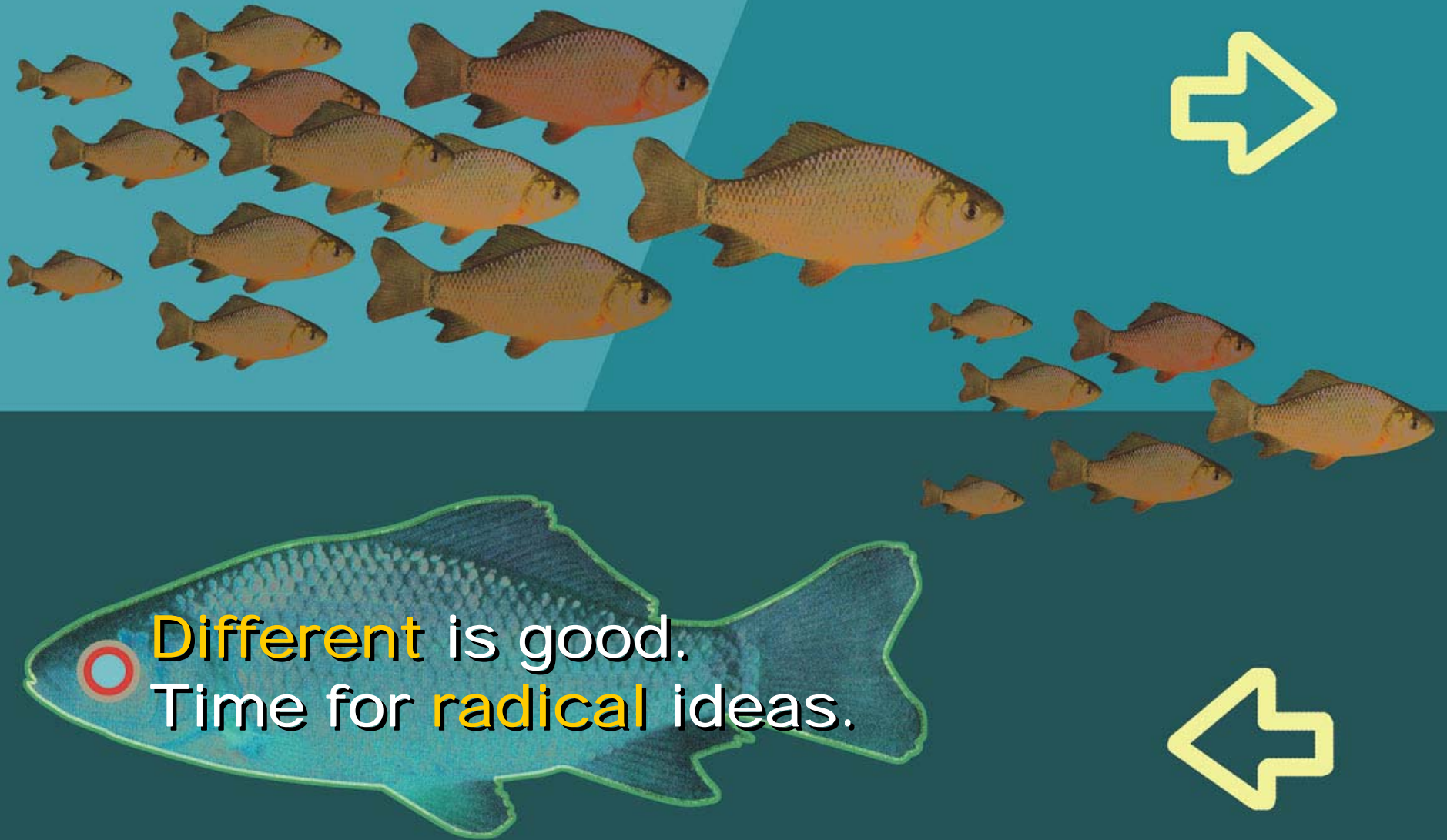


Rutenbar's Rule—Revisited

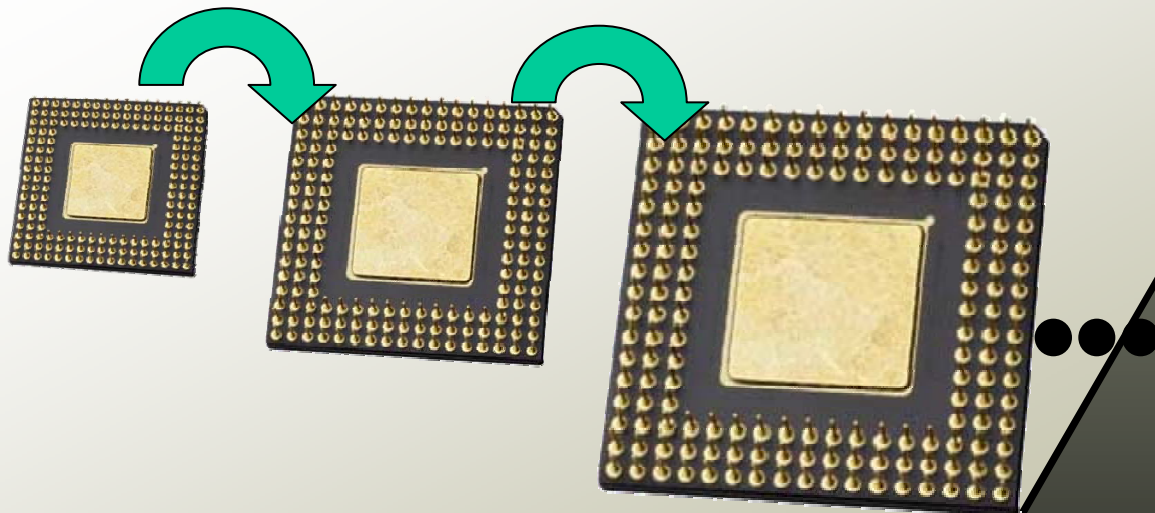
- The taller the tool-chain, the more difficult for innovation in 1 tool to “survive the flow”



"Tall Tool-Chains" Advice



Big Challenge #3: Big Systems

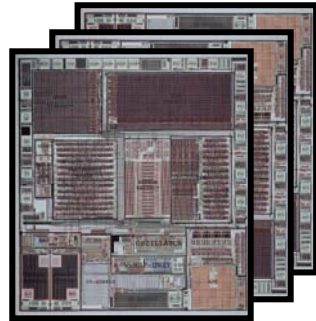


■ **Challenges
in complexity**



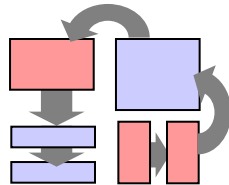
How To Explain (*Teach*) This...?

Systems



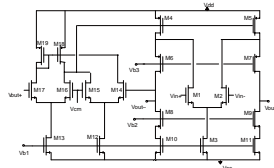
10M – 10B devices

Architectures



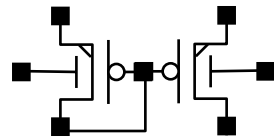
10K – 1M devices

Basic blocks



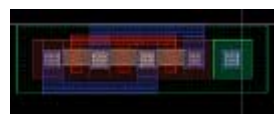
100-1000 devices

Circuits



10 devices

Devices



1 device

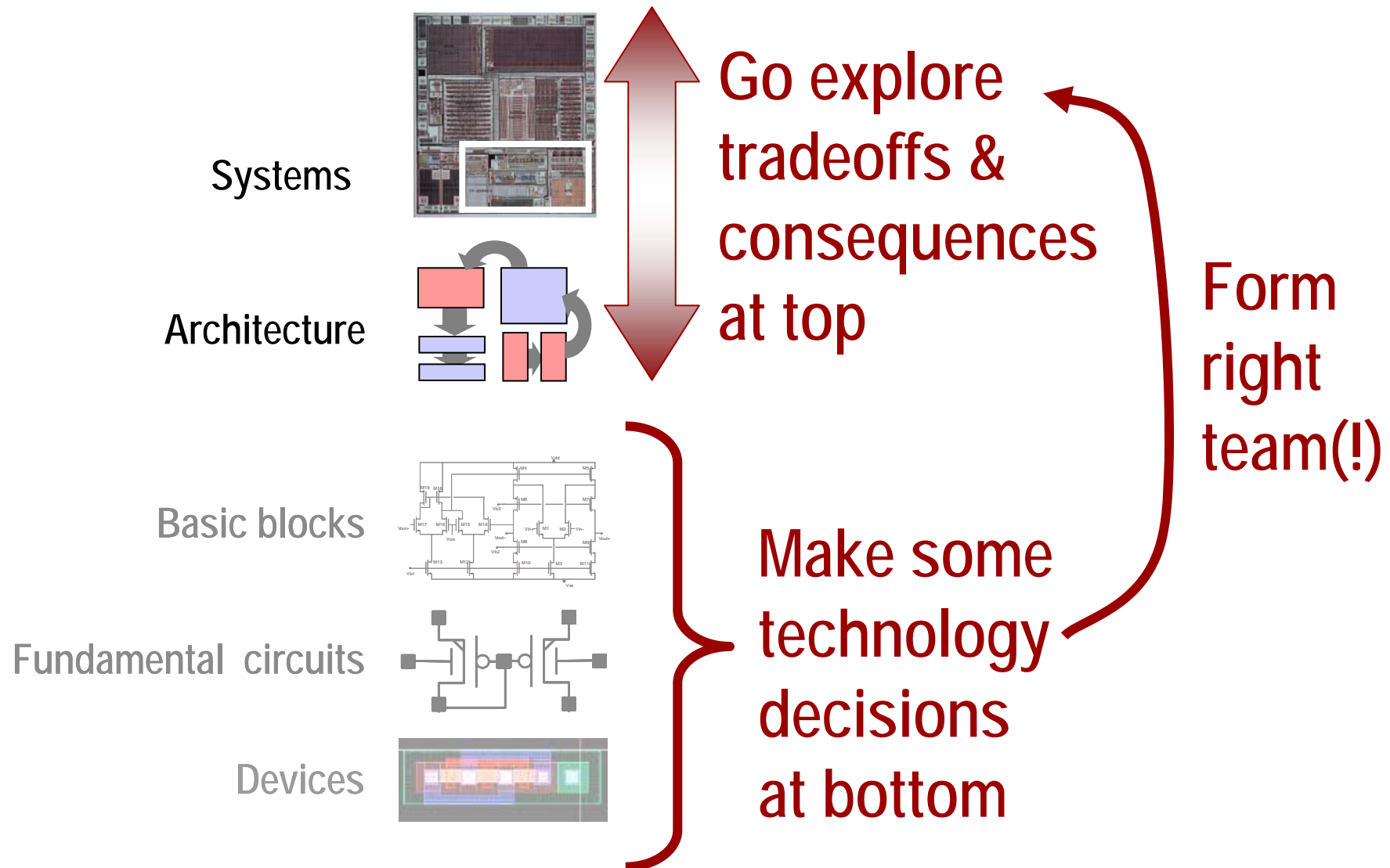
Unique
problems
as we go
"UP"

“Big Systems” Advice



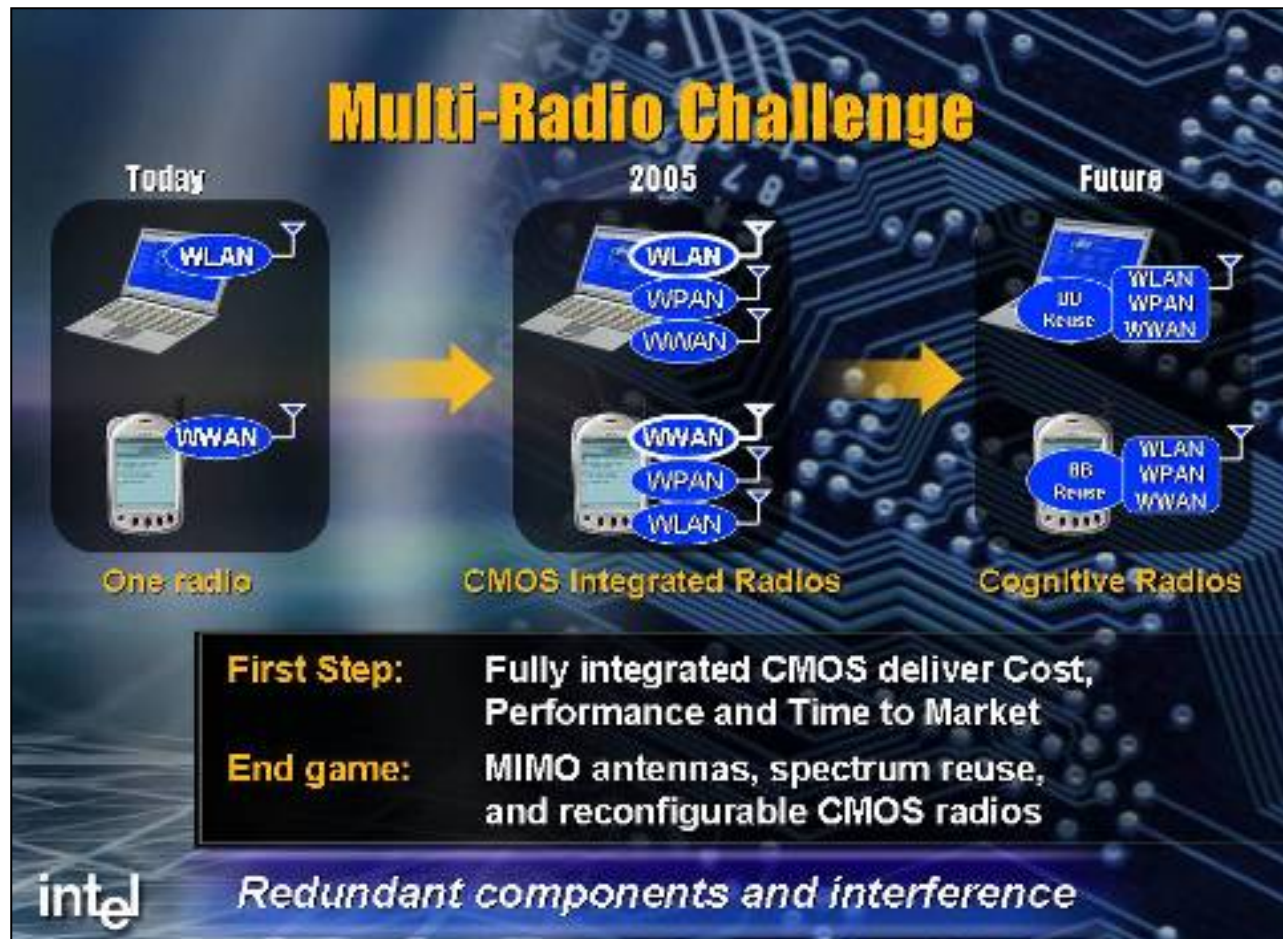
- **How do you learn to be a tightrope walker?**
 - **Buy a book? A Powerpoint talk? Buy the DVD?**
- **No: you just go do it, try it, practice it**

Same with System Design: Just Do It



“Big Team” Example: Parallel Radios

- From Pat Gelsinger, Senior VP of Intel

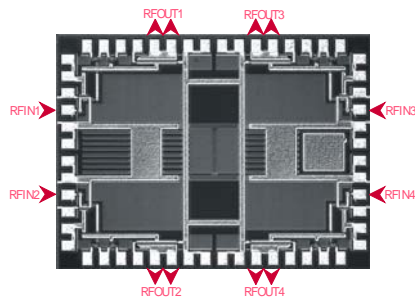


[Source: Pat Gelsinger, Intel]

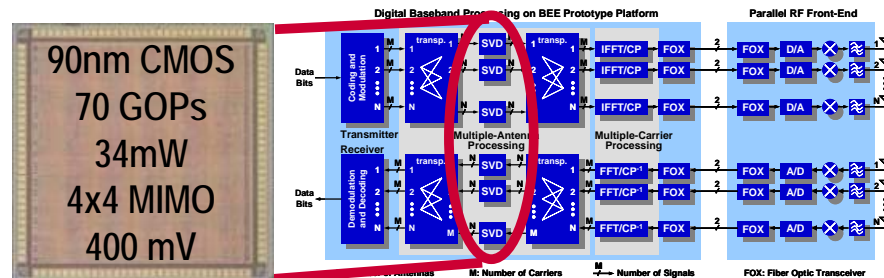
"Big Team" Ex: Parallel Radio Designs

- **Multi-university effort: Berkeley + MIT**
 - US national FCRP Focus Center for Circuit & System Solutions (C2S2), funded by govt + semiconductor industry

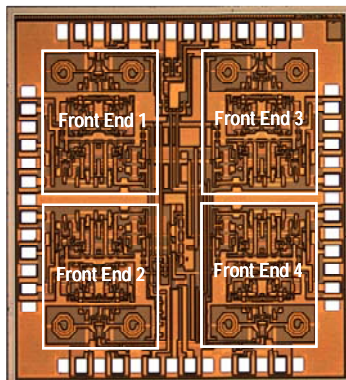
Parallel SiGe power amps



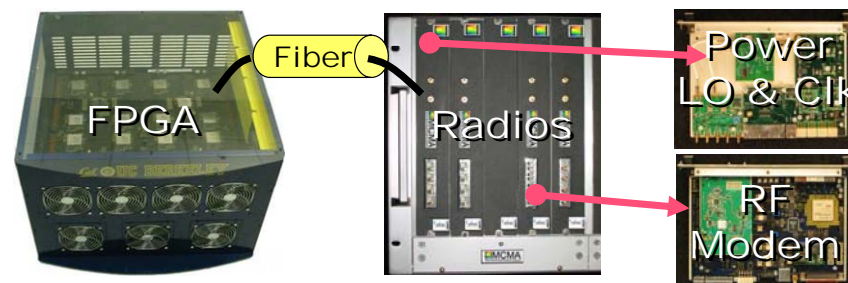
Parallel CMOS radio baseband DSP



Parallel SiGe RF frontends

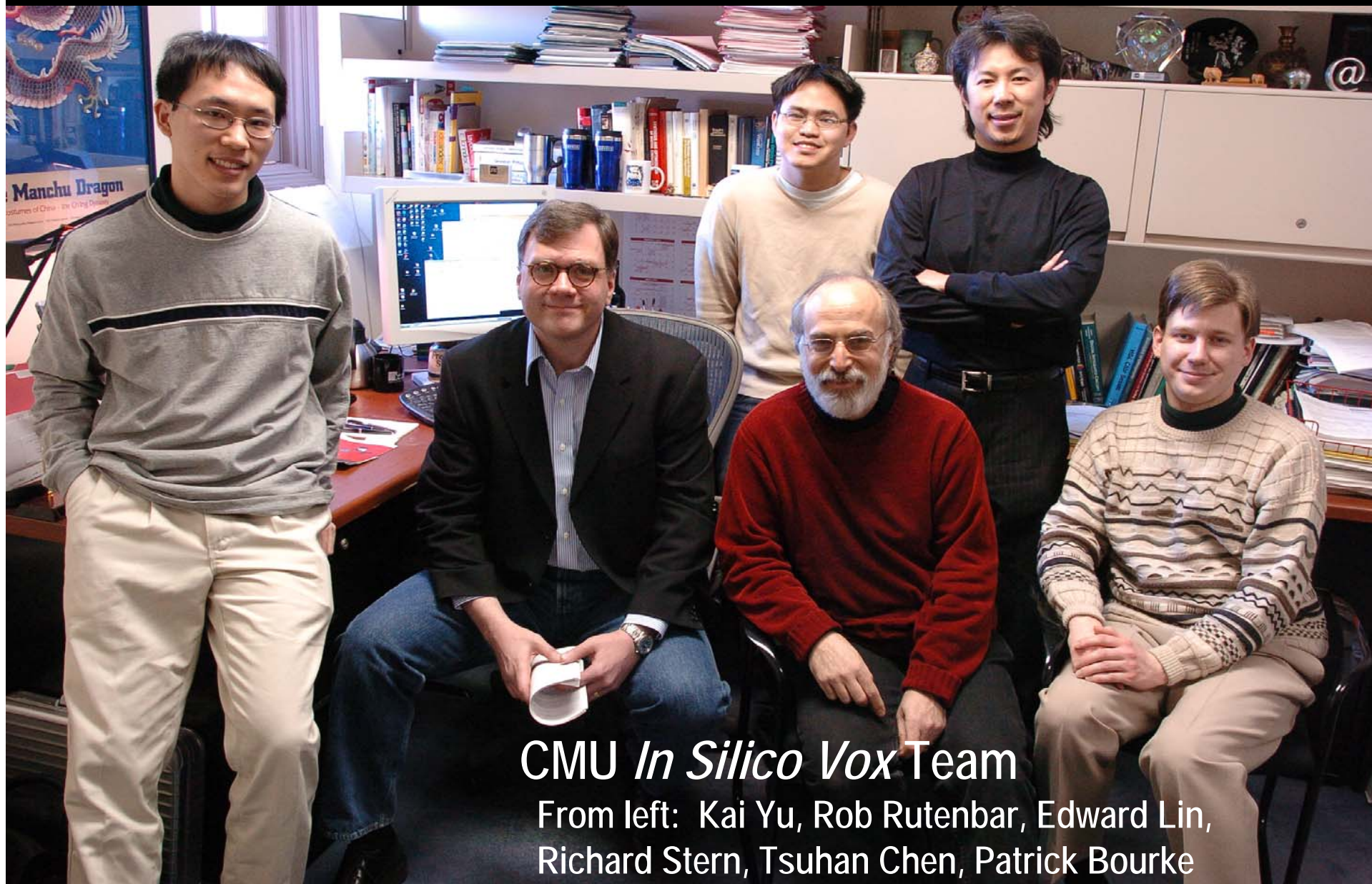


Parallel Radio Emulation System: BEE



[Charles Sodini, Greg Wornell, MIT] [Bob Brodersen, Bora Nikolić UCB]

But A Small Team Can Do It Too...



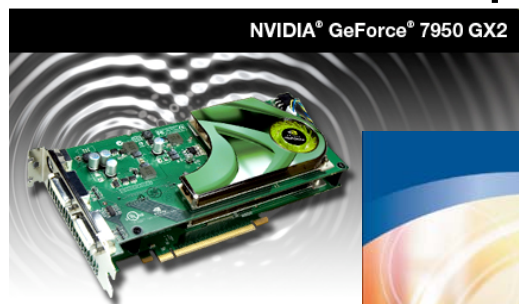
CMU In Silico Vox Team

From left: Kai Yu, Rob Rutenbar, Edward Lin,
Richard Stern, Tsuhan Chen, Patrick Bourke

In Silico Vox: Speech Recognition in Silicon

- Paint pixels in software?
- No! Graphics chips
- So why are all today's best speech recognizers done in *software*?

True on the desktop



<http://www.nvidia.com>

& cell



<http://www.mtekvision.com>



Can we do better?

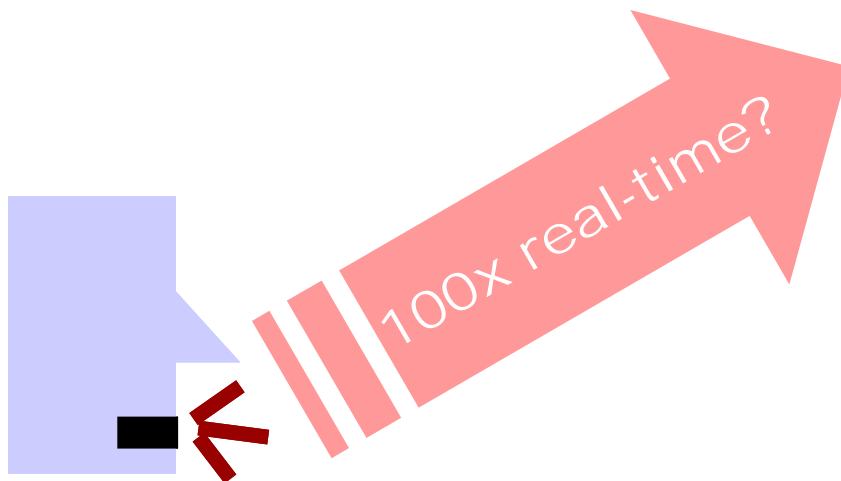
Next-Gen Apps Need $>100\times$ Improvement

Audio-mining

- Very **fast** recognizers
–faster than realtime
- App: search media streams (DVD) quickly

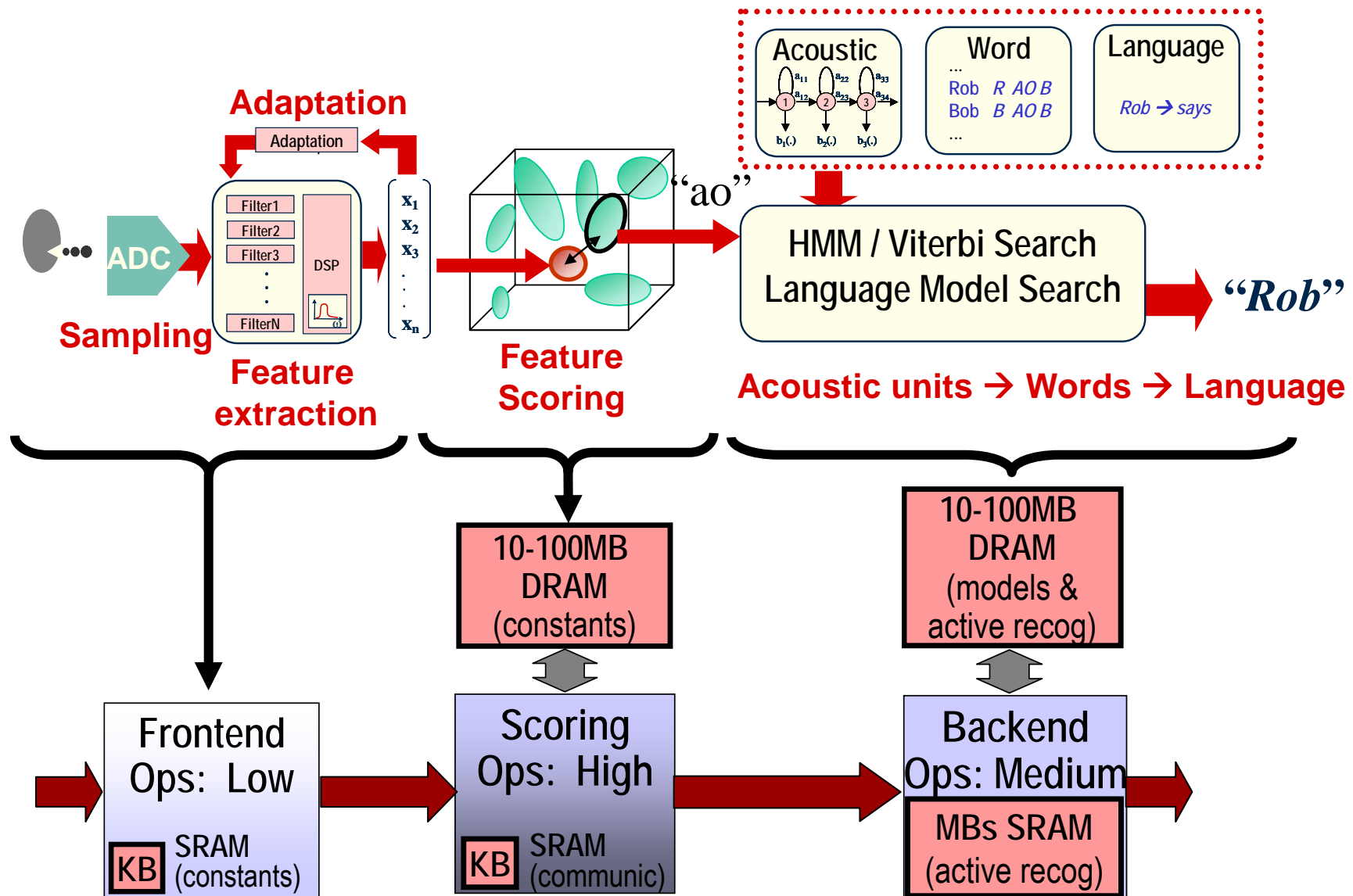
Hands-free appliances

- Very **portable** recognizers
–high quality on $\ll 1$ watt
- App: interfaces to small devices, cellphones



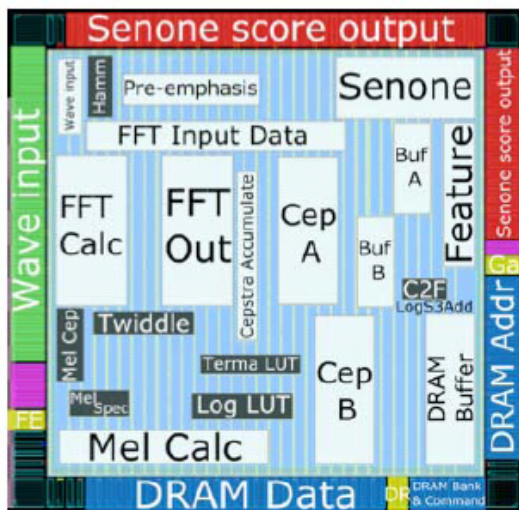
"send email to rob - let's do lunch."

Speech: Complex Task to do in Silicon

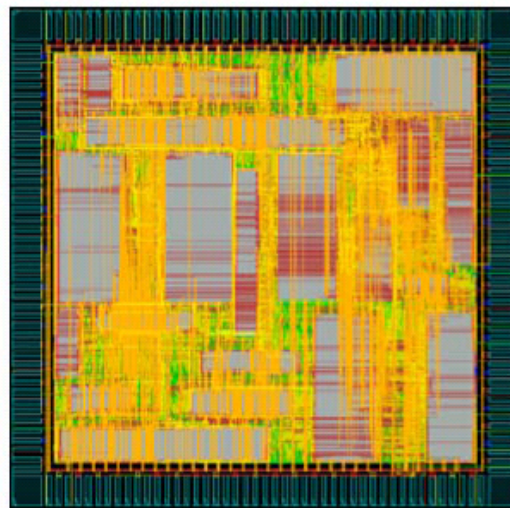


Pieces of Design: Great Class Projects

- CMU student team: Patrick Chiu, David Fu, Mark McCartney, Ajay Panagariya, Chris Thomas



Floorplan



Final Layout

Area	11.16 mm ² core / 16.09 mm ² chip
Effective Utilization	53.32%
Cell Rows	657
Cells	67354
Pins	225358
IO Pins	94
Nets	79382
Avg. Pins/Net	2.84
Nets	
(Internal)	77977
(External)	94
Connections	
(Internal)	146621
(External)	188
Total net length	6.00 m
(X)	2.59 m
(Y)	3.40 m
Power Supply	1.98 V
Average Power	19.8 mW
(switching)	11.78 mW
(internal)	7.98 mW
(leakage)	0.036 mw
Power by clock domain	
Frontend	2.018 mW
Gaussian	14.25 mW
DRAM	2.57 mW
Unclocked	0.96 mW
Power by cell category	
Core	19.5 mW
Block	0.29 mW
IO	0 mW
Worst IR drop	0.012 V

Final Stats

CMU *In Silico Vox* Project: FPGA Results

- ***Most complex*** recognizer ever mapped to hardware
 - [Lin, Yu, Rutenbar, Chen, HOTCHIPS 2006]



“Big Systems” Advice: Tightrope Walking



- **How to learn to deal with system complexity?**
- **Pick a complex system. Deal with it.**

Concluding Thought

- “One thing we know about creativity is that it typically occurs when people who have mastered two or more quite different fields use the framework in one to think afresh about the other...

Marc Tucker, *Tough Choices or Tough Times*

- Lithography + EDA optimization
 - ... Semiconductors + Computational finance
 - ... Speech recognition + Custom silicon
 - ... Many creative combos await discovery

Thank You!

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